Principles of Micro- and Nanofabrication for Electronic and Photonic Devices

Cleanroom, Wafer Clean and Gettering

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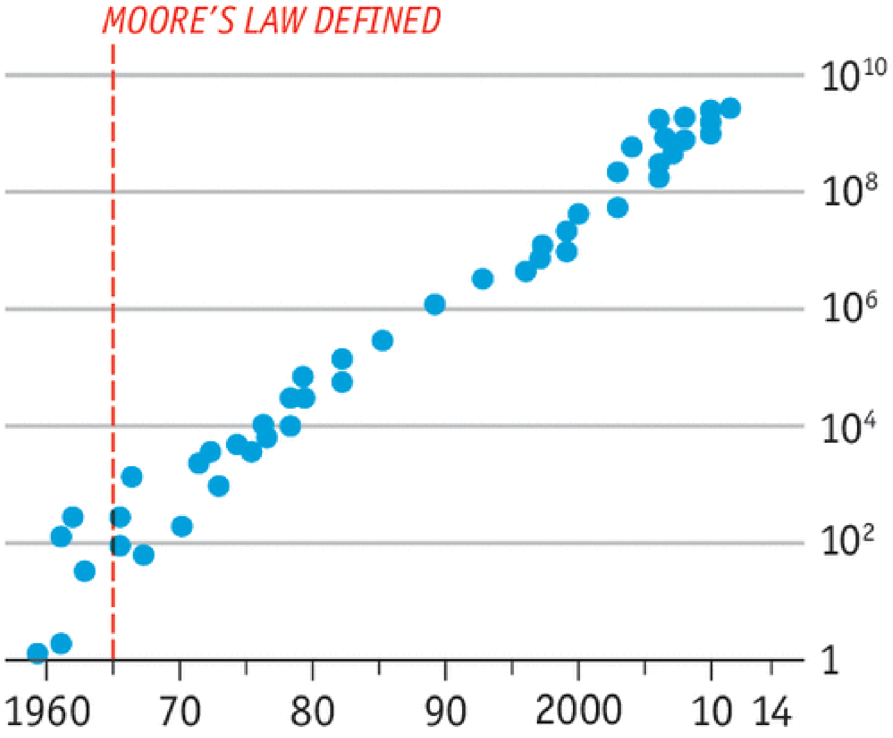
Integrate Circuits

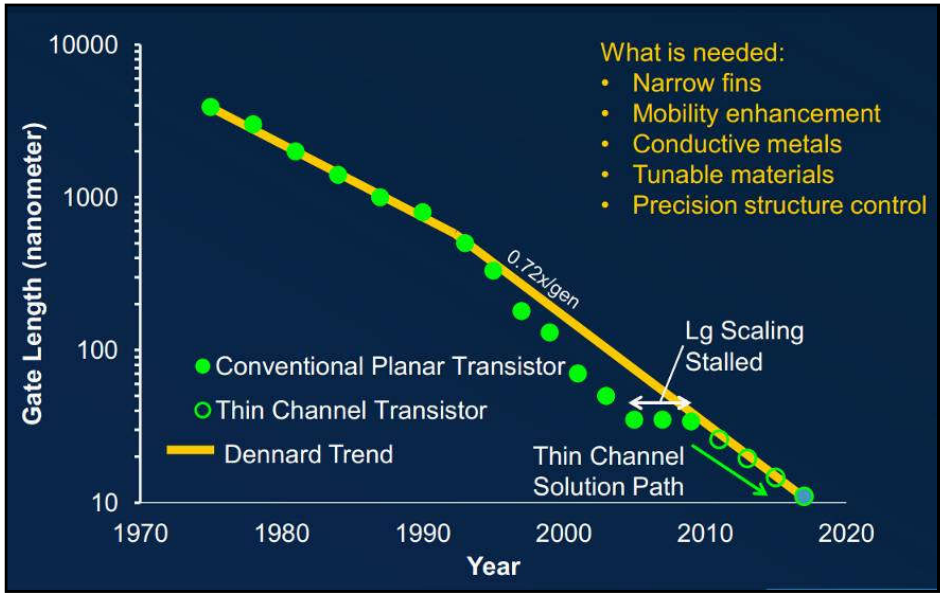
- **Moore's law**



Source: Intel

*Central processing unit

Economist.com

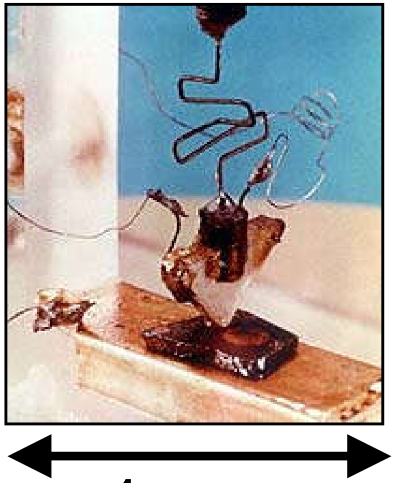


transistor number ↗

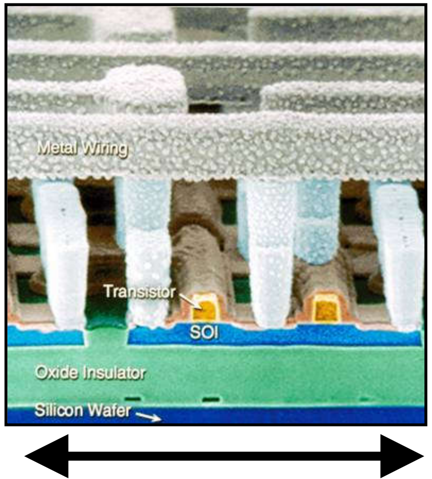
transistor size ↘

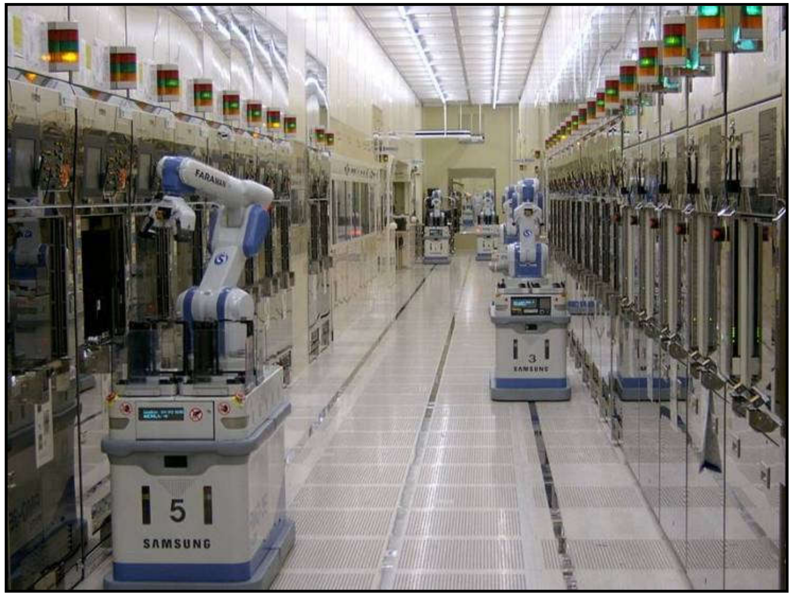
Technology Evolution

1947



today



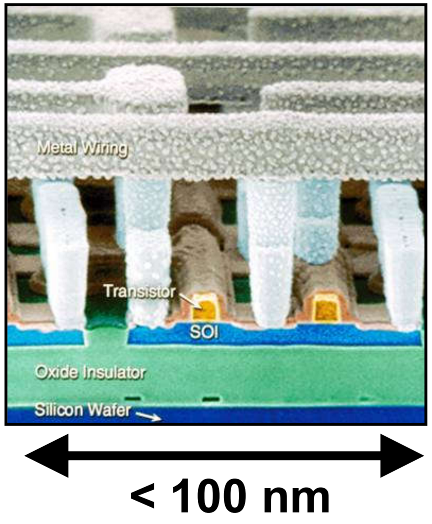


Factory Evolution

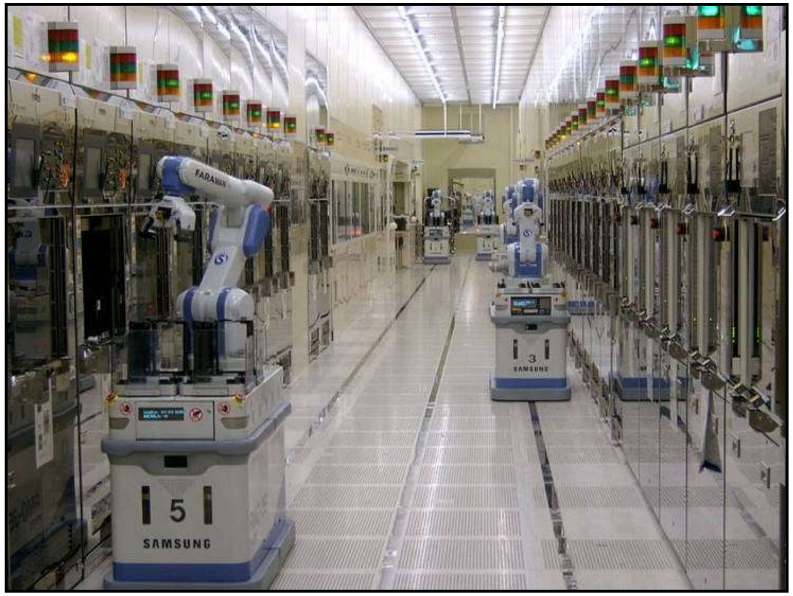
- cost of new fab
  - 1967 2 million $
  - 2010 10 billion $

Video TSMC

today

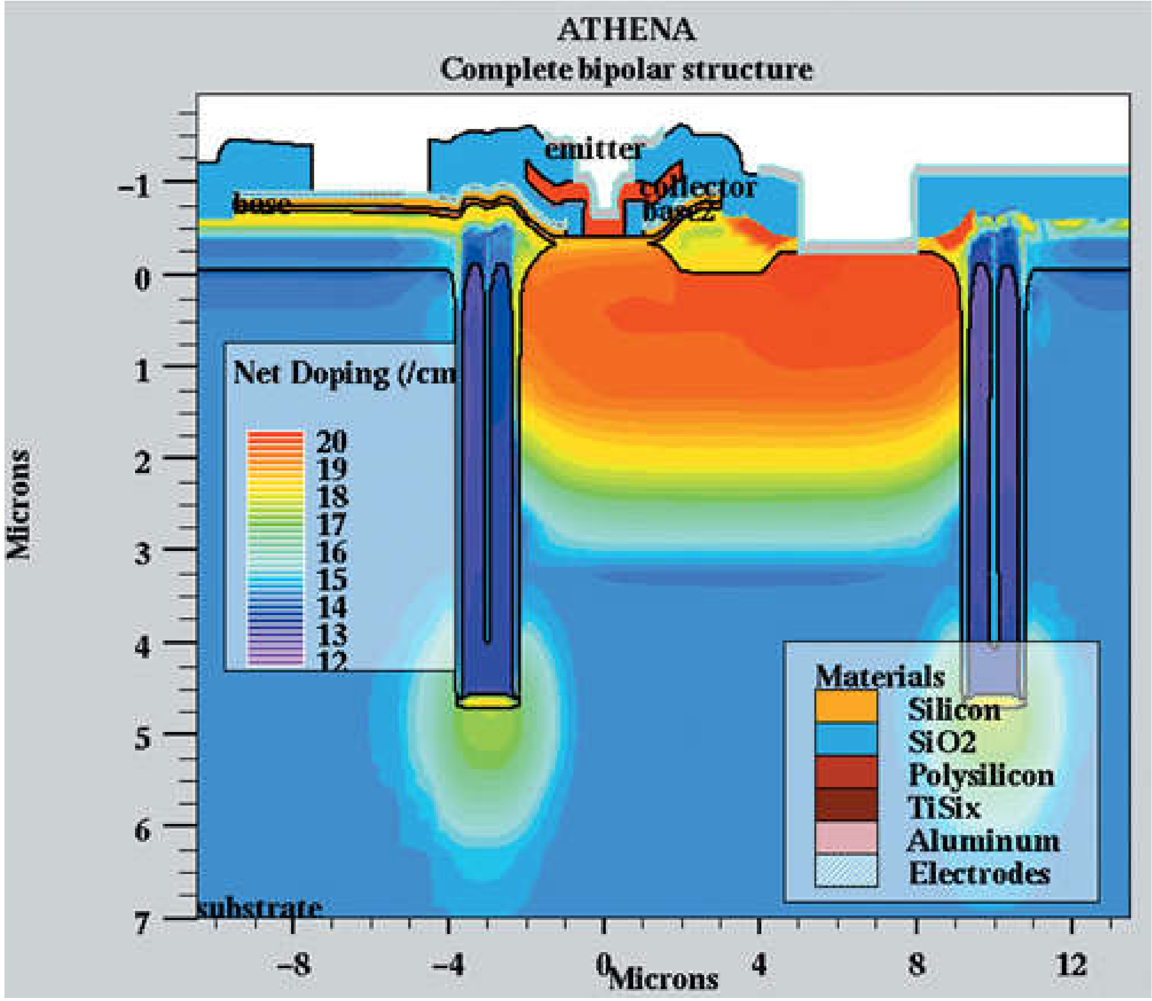


2016 长江存储，武汉
24 billion $$



Process Simulations

- **Silvaco**



https://www.silvaco.com/products/tcad/process_simulation/victory_process/victory_process.html

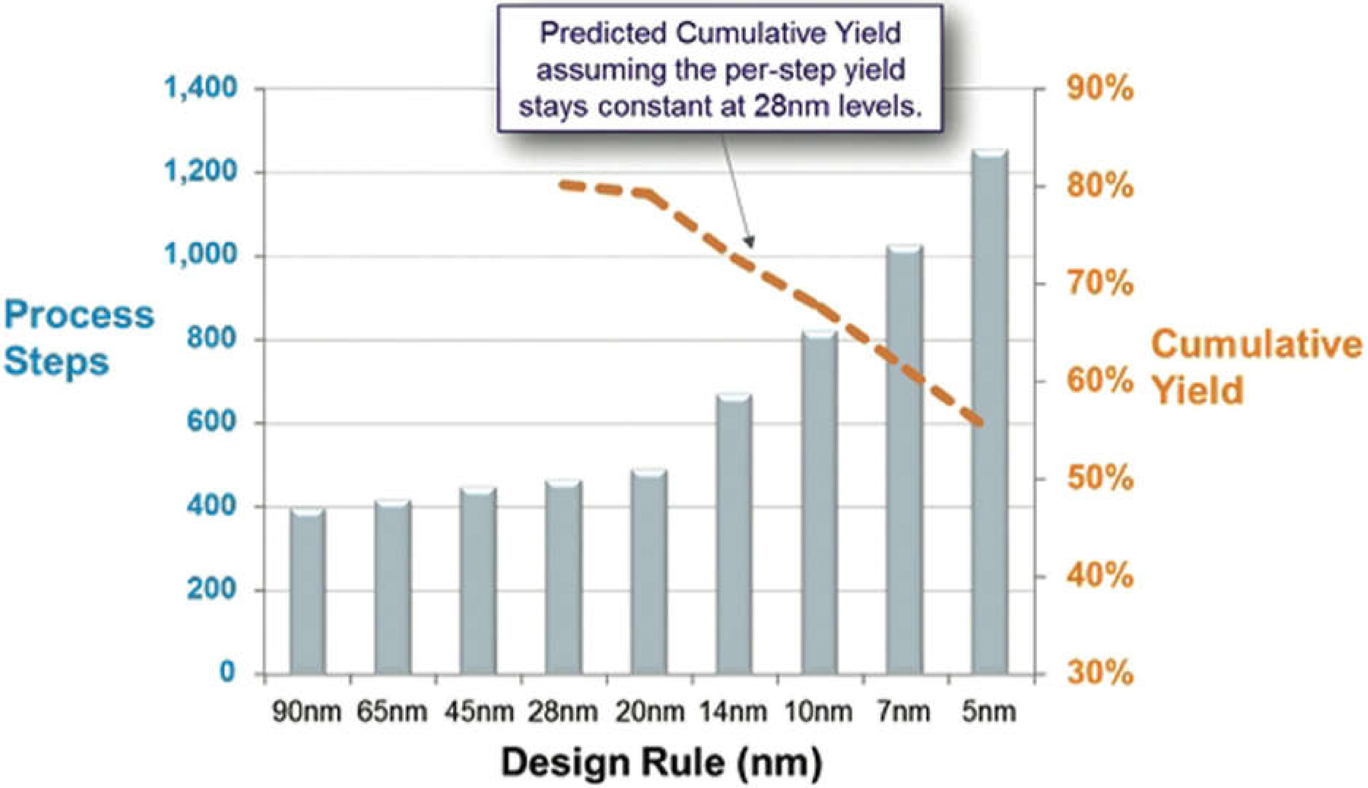
Manufacturing Yield

- **Yield: rate of success**

assume yield = 99% per step:

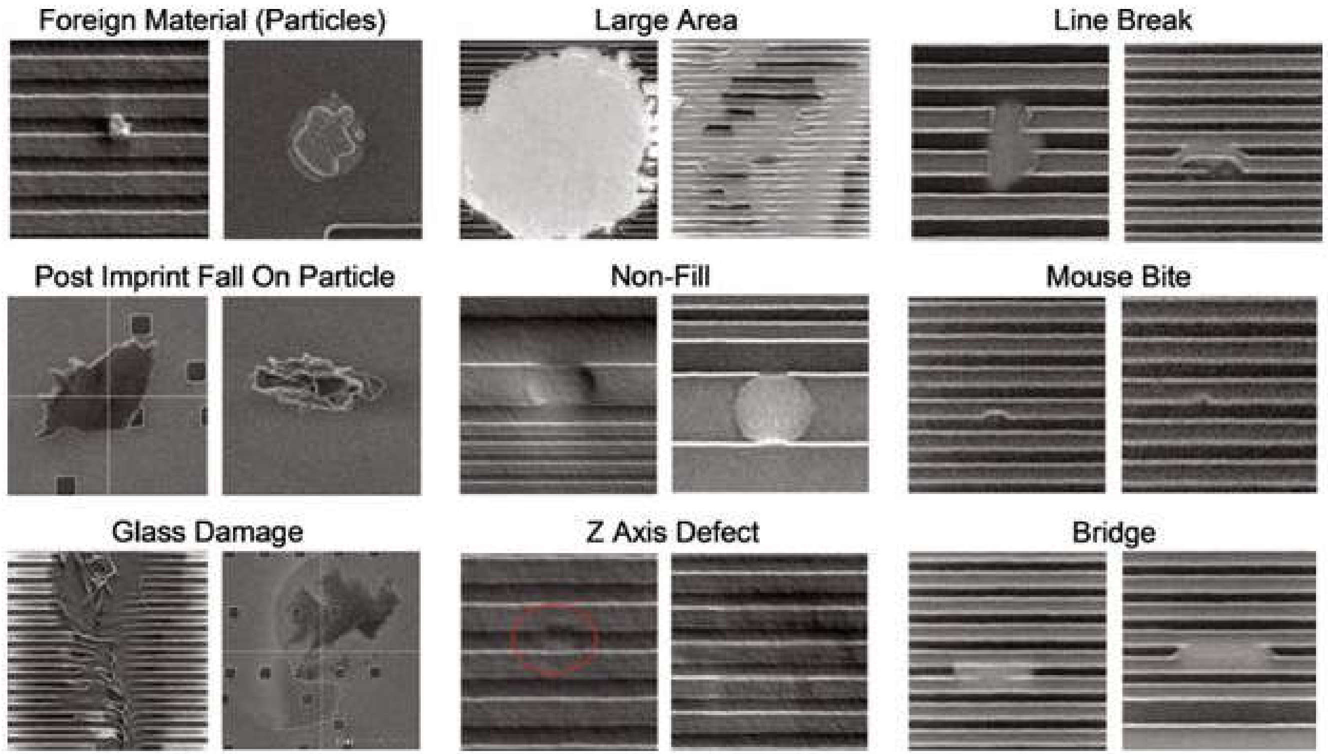
$0.99^4 = 0.96$

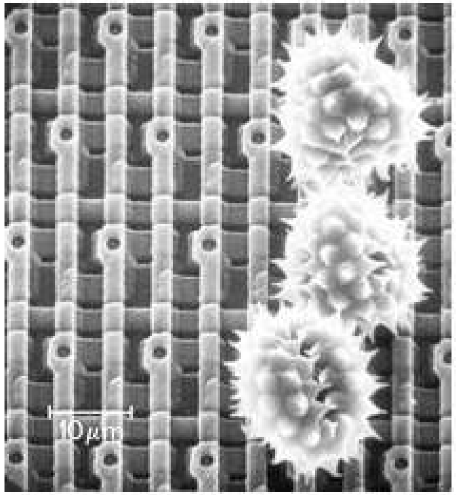
$0.99^{400} = 0.02$

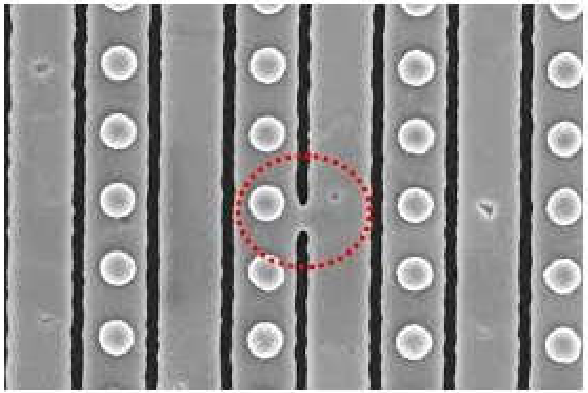


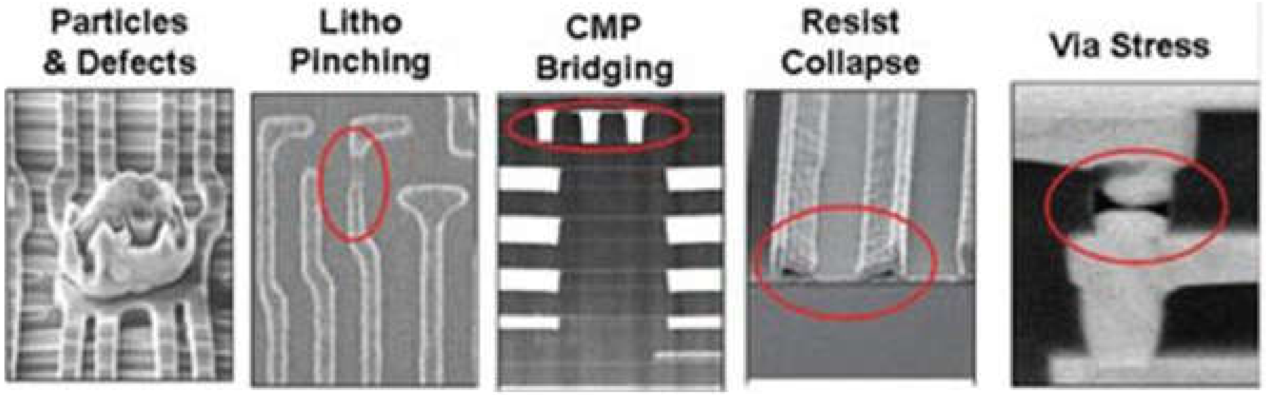
every 1% yield means $$$

Manufacturing Defects


Foreign Material (Particles)
Large Area
Line Break
Post Imprint Fall On Particle
Non-Fill
Mouse Bite
Glass Damage
Z Axis Defect
Bridge

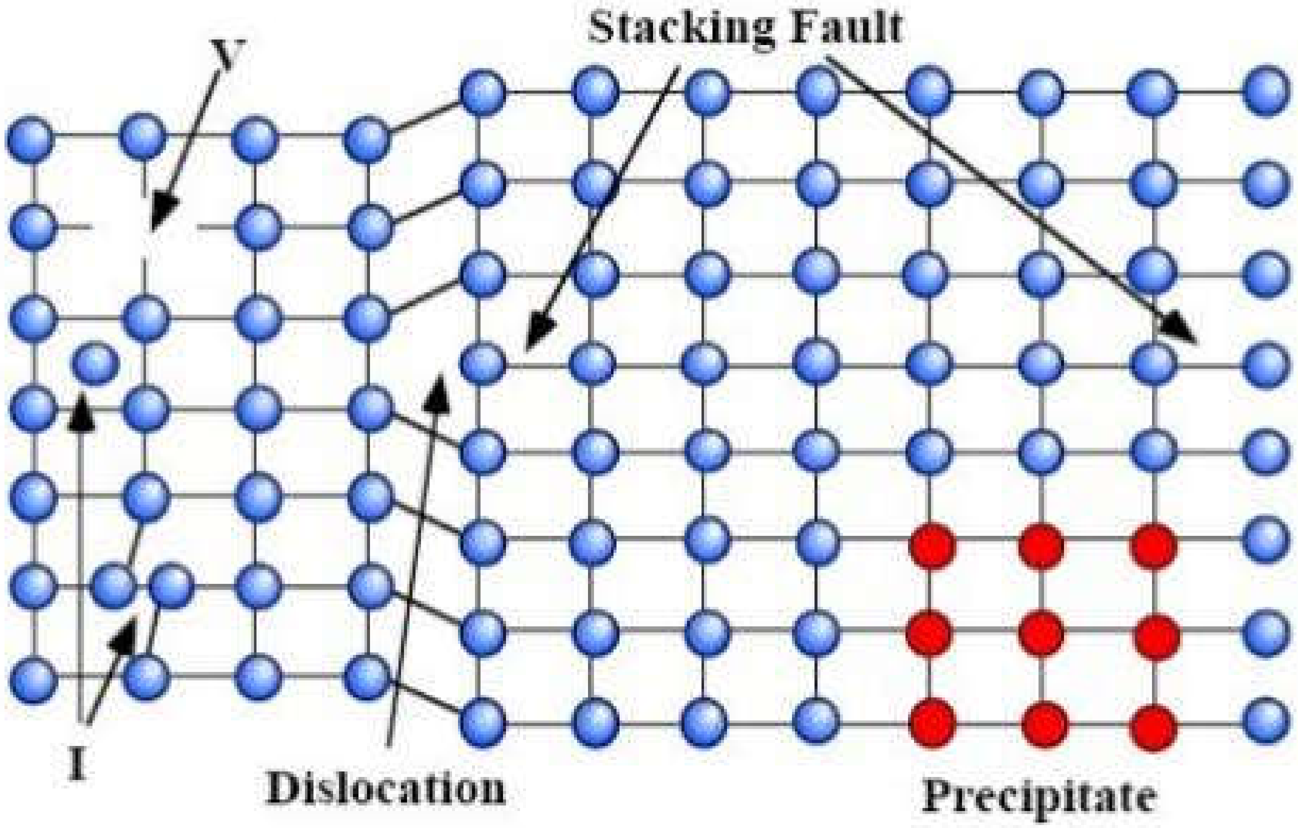





Particles & Defects
Litho Pinching
CMP Bridging
Resist Collapse
Via Stress

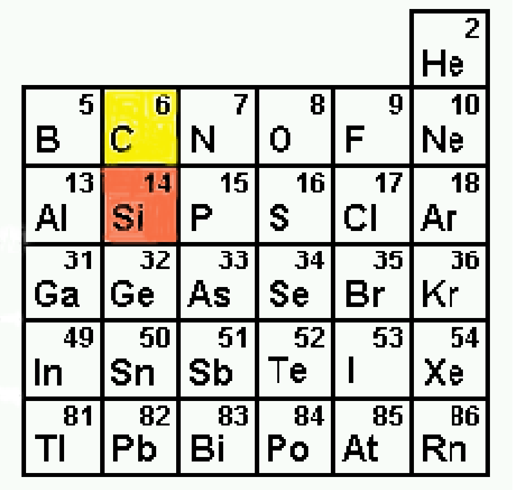
Defects in Silicon

- Point Defects e.g. Vacancies (V), Interstitials (I)
- Line Defects e.g. Dislocations
- Area Defects e.g. Stacking Faults ("extrinsic" or "intrinsic" form along {111} planes)
- Volume Defects e.g. Precipitates, Collection of Vacancies



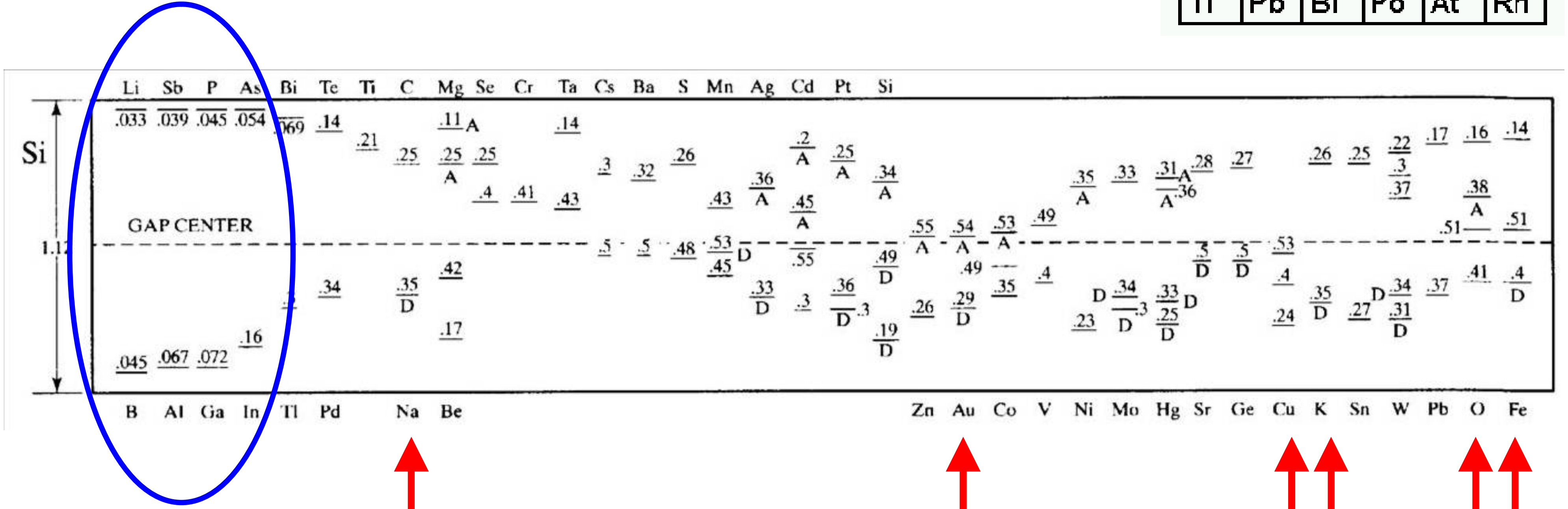
Defects in Silicon

Q: why?



					2 He
5 B	6 C	7 N	8 O	9 F	10 Ne
13 Al	14 Si	15 P	16 S	17 Cl	18 Ar
31 Ga	32 Ge	33 As	34 Se	35 Br	36 Kr
49 In	50 Sn	51 Sb	52 Te	53 I	54 Xe
81 Tl	82 Pb	83 Bi	84 Po	85 At	86 Rn

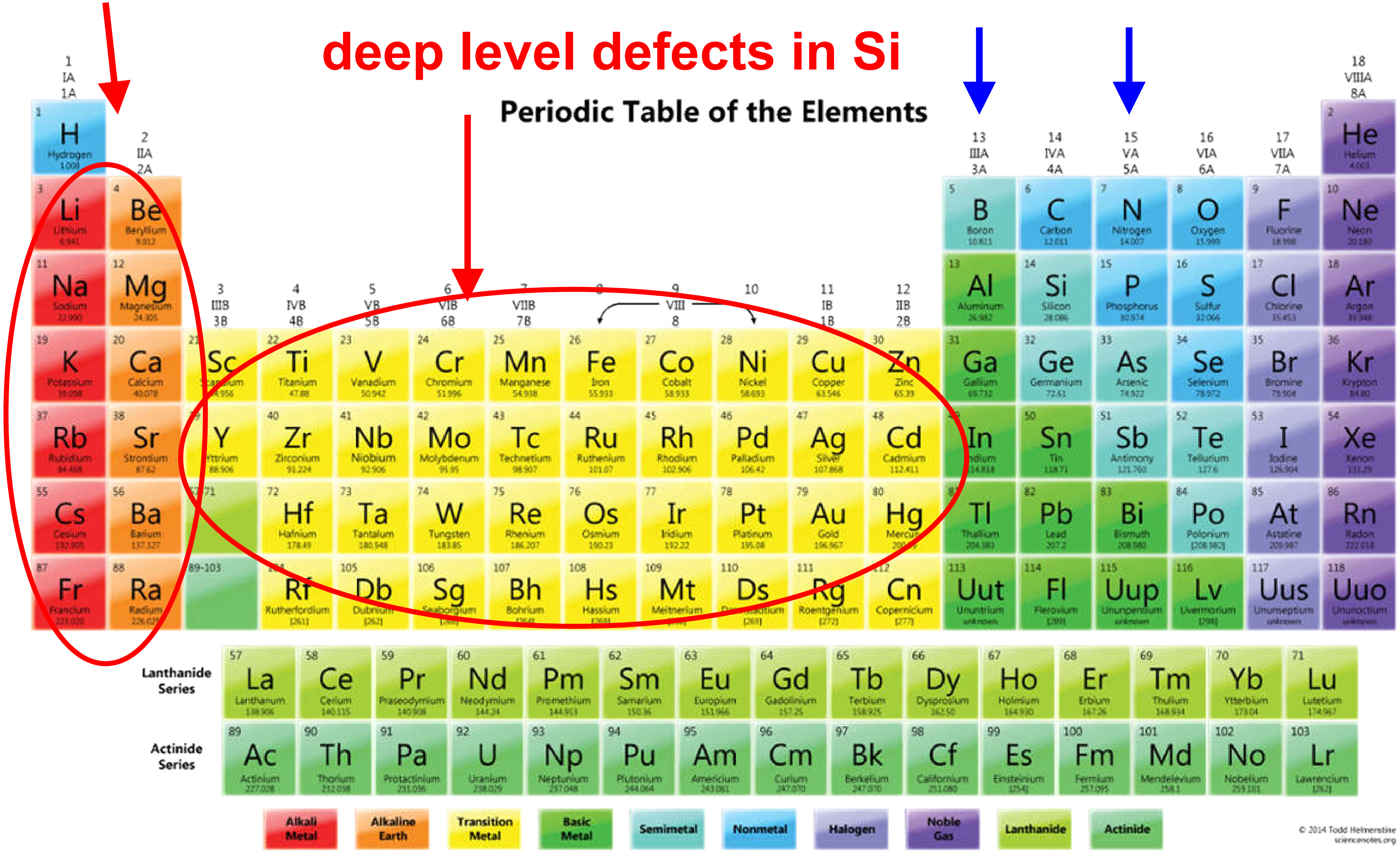
dopants



deep level defects

Na, K, Au, Cu, Fe, O, ...

Defects in Silicon



ions in gate oxide

deep level defects in Si

dopants

Periodic Table of the Elements

Defects in Silicon

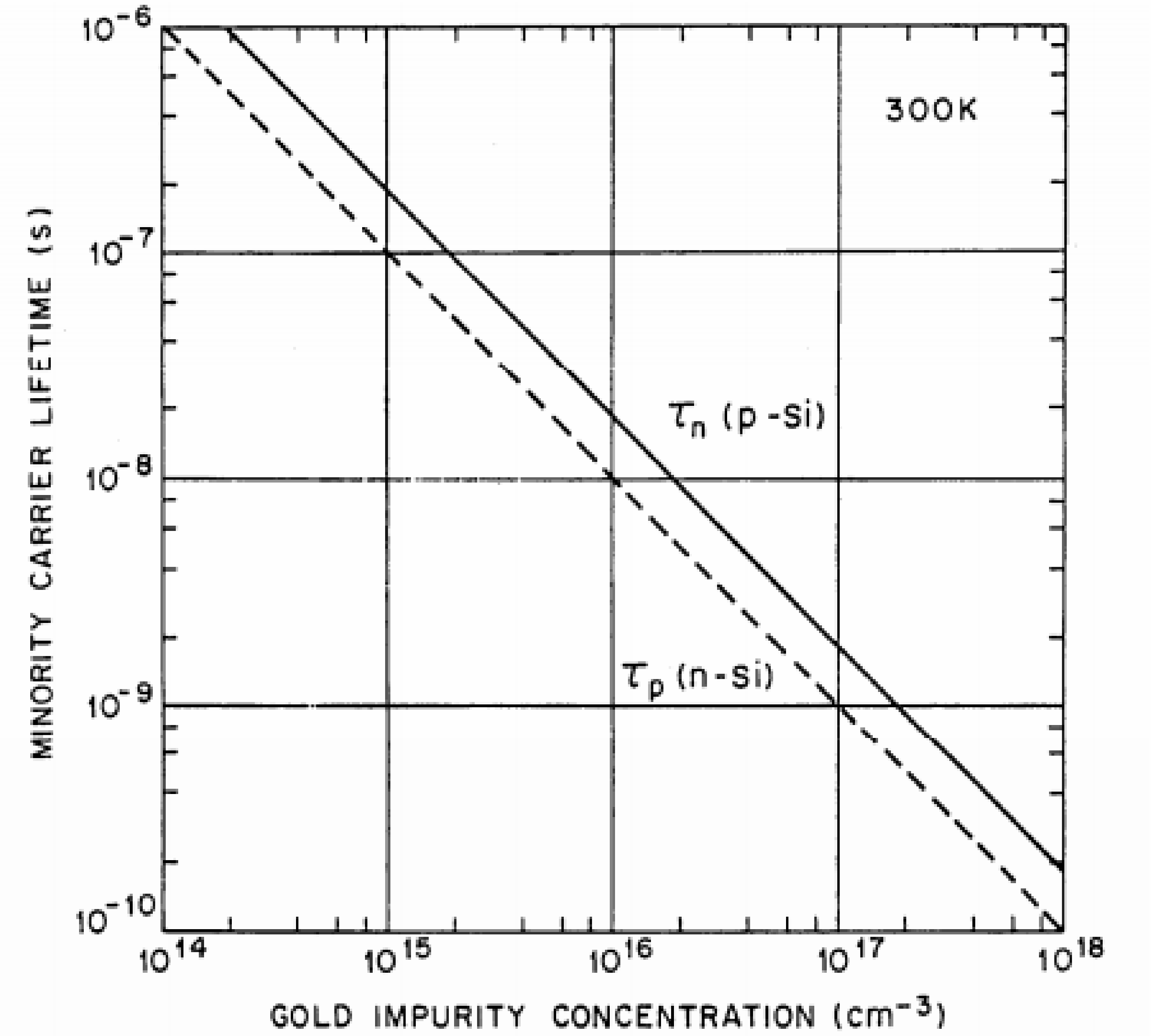


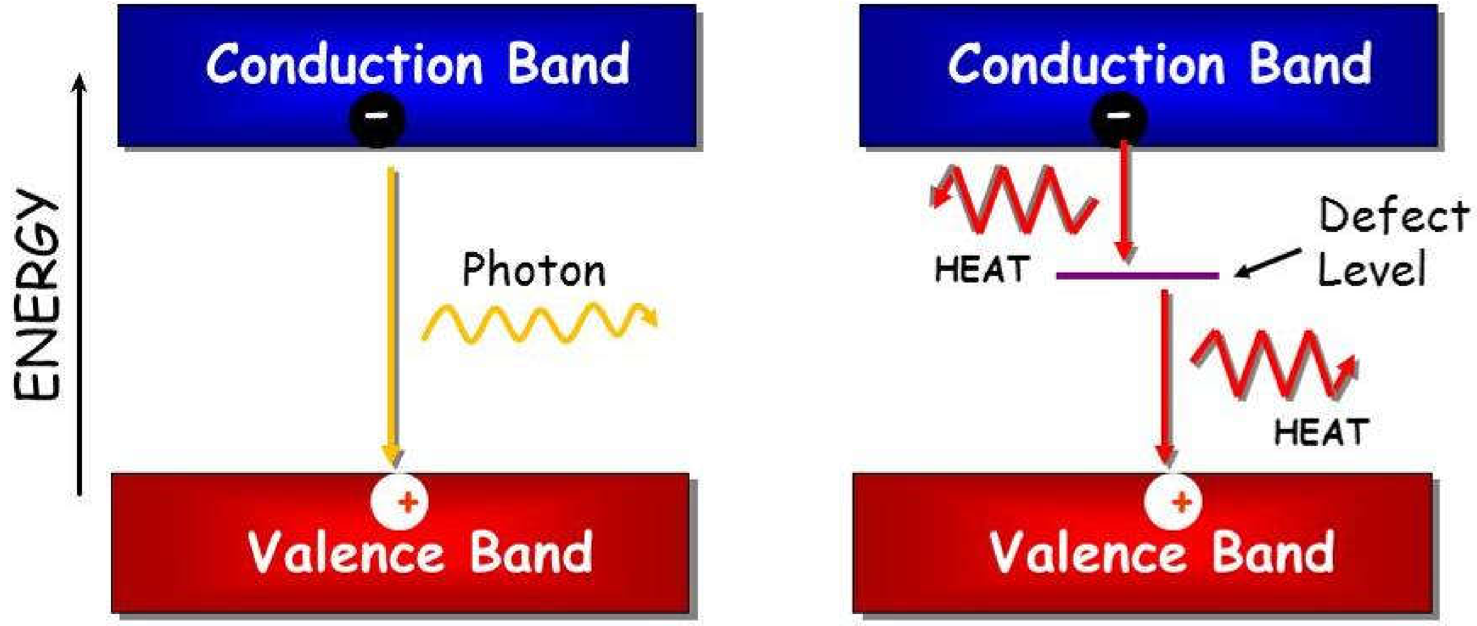
Fig. 16 Recombination lifetime versus gold impurity concentration in silicon.[8]

Deep level defects (e.g. Au) reduce minority carrier lifetime in Si

bad for solar cells

Defects

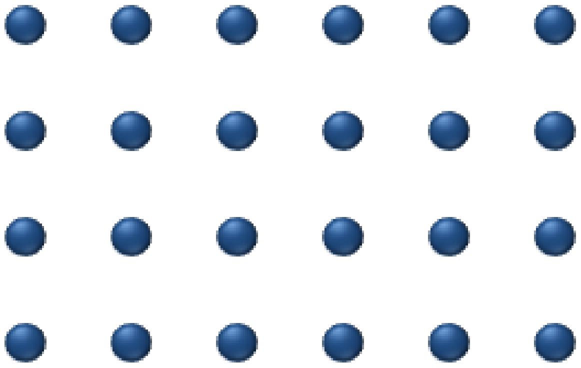
recombination at defect sites
reduce efficiencies of LEDs / solar cells



Diffusion of Defects

Liquid

Solid



C concentration (mol/m^3)

J diffusion flux (mol/m^2/s)

D diffusivity (m^2/s)

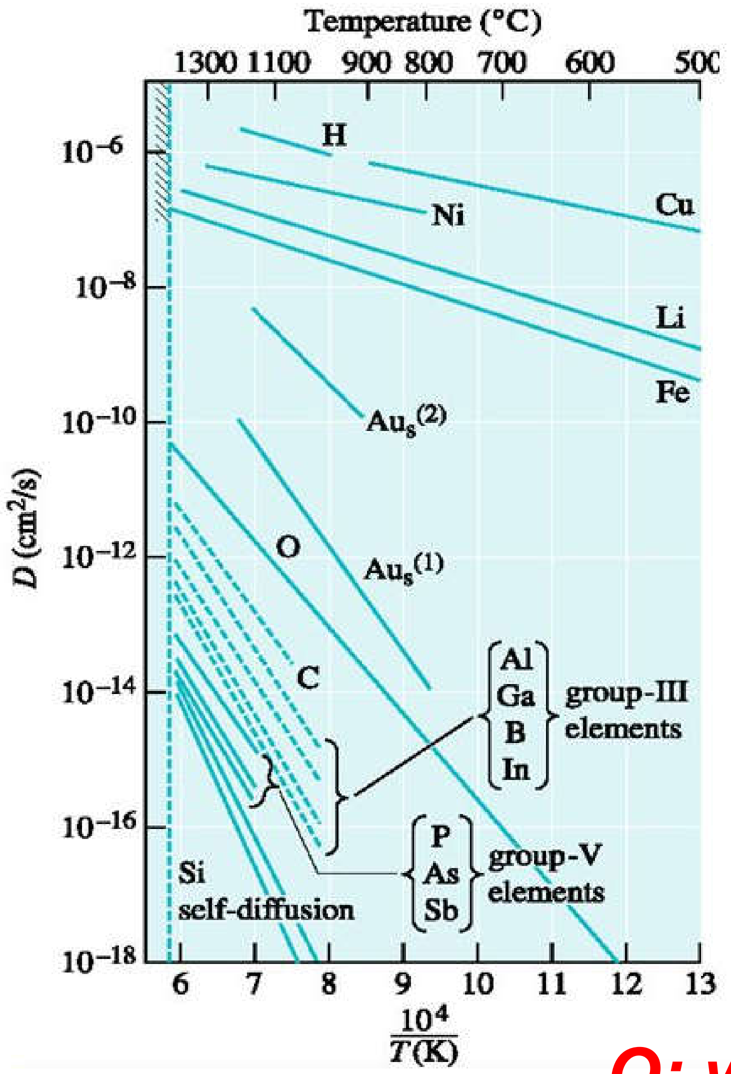
Diffusion of Defects

- **Diffusivity (扩散系数) *D***
  - rate of spread
  - unit: $\mathrm{cm^2/s}$

$$D = D_0 \exp\left(-\frac{E_A}{kT}\right)$$

- **Diffusion length *L***

$$L = \sqrt{Dt}$$



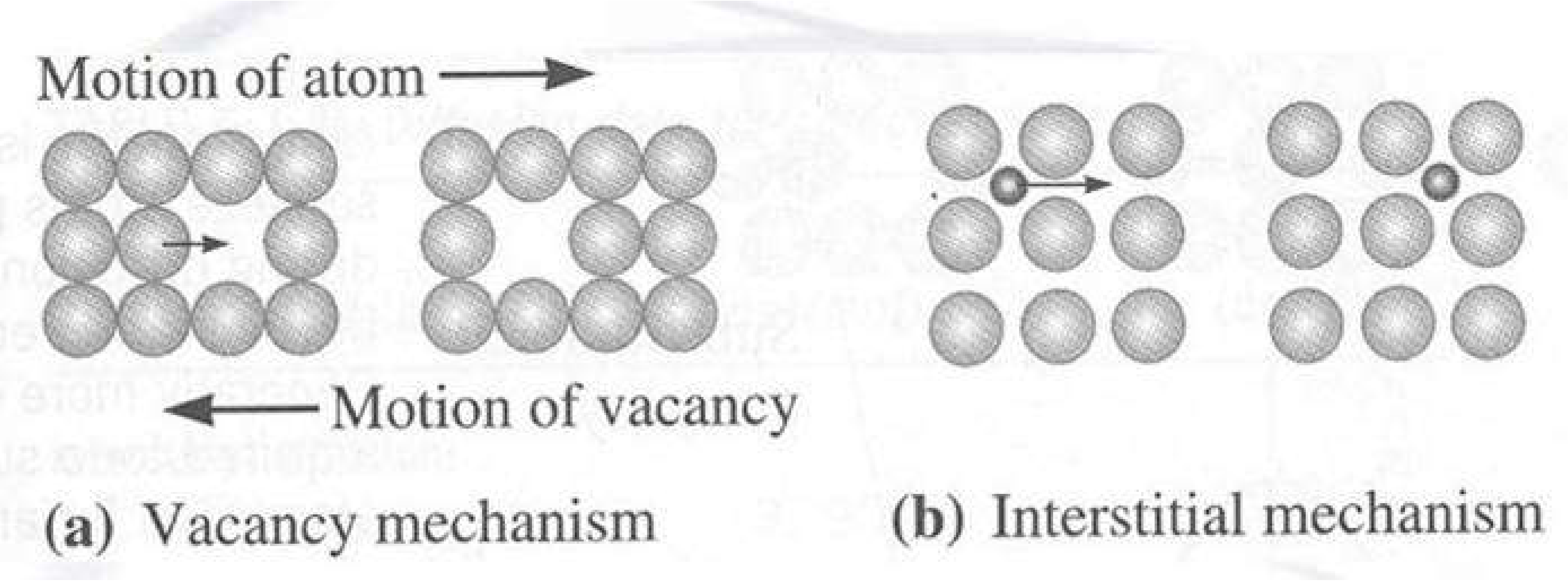
fast

slow

Q: why?

diffusivity of defects in Si

Defect Diffusivity in Silicon



Si, B, P, As, Sb, ...

Cu, Fe, Li, H, Au, ...

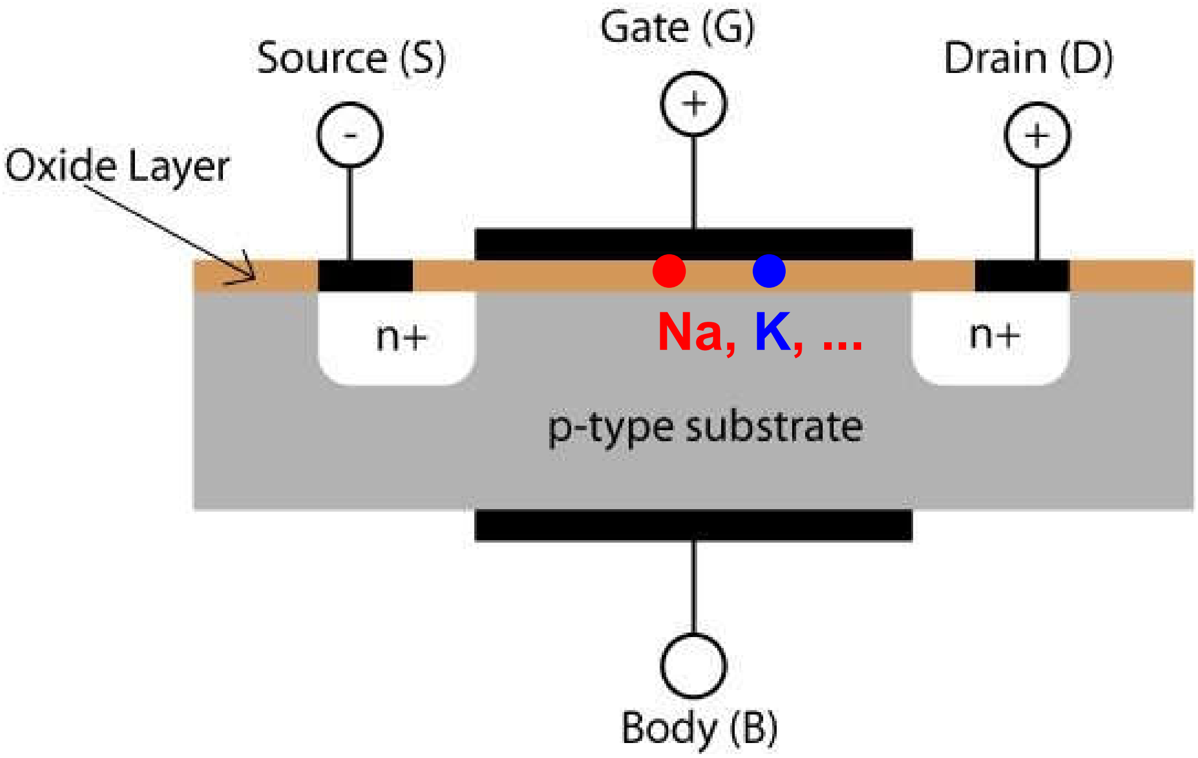
Slow

Fast

Defects in Oxide

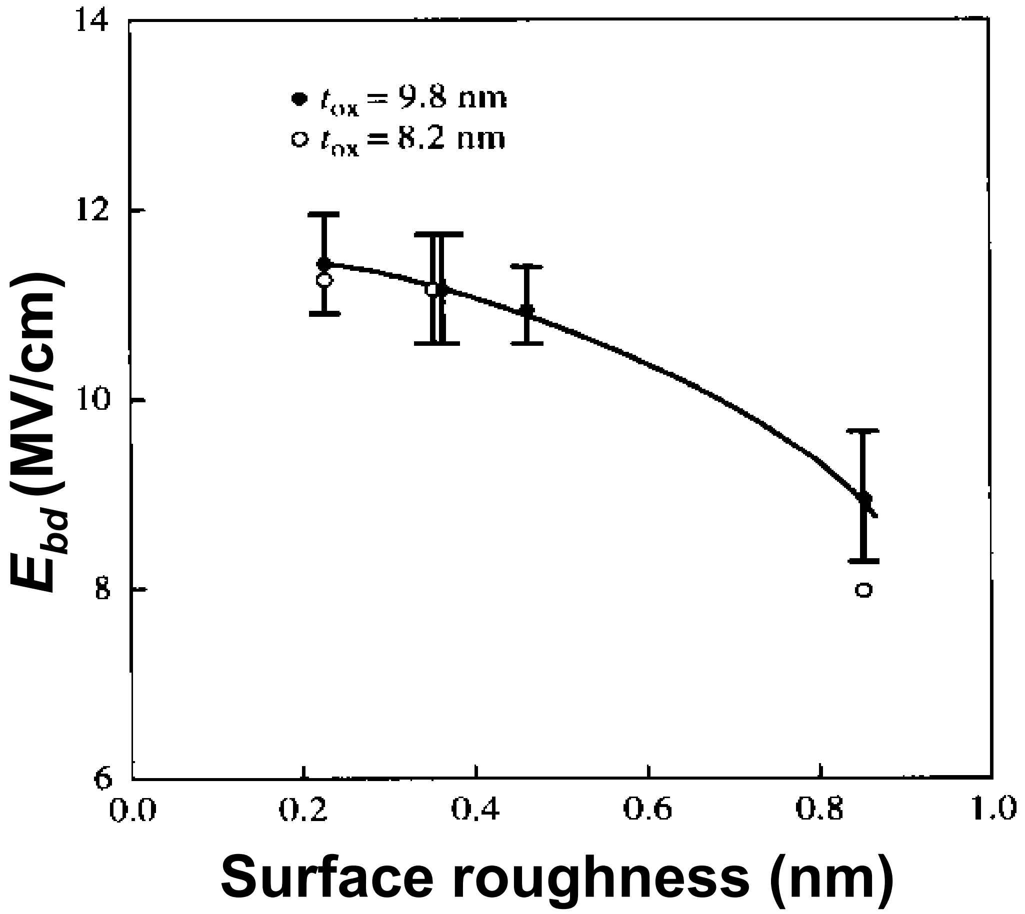
defect density

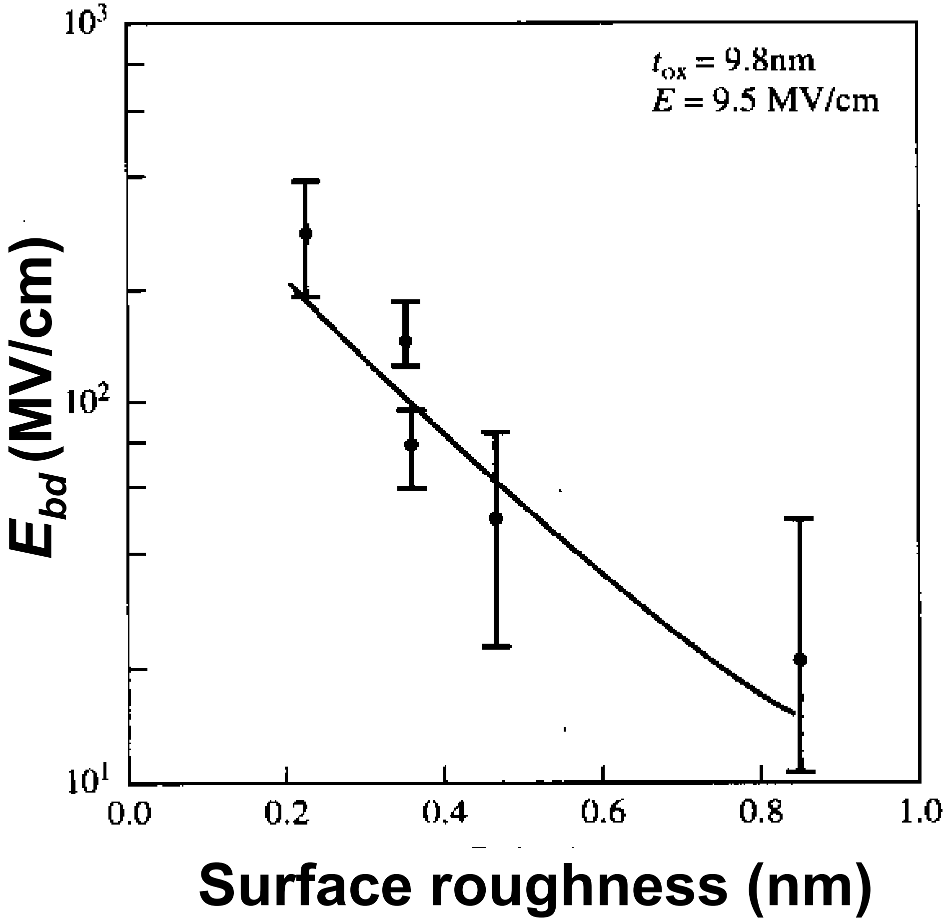
$$V_{th} = V_{FB} + 2\Phi_f + \frac{\sqrt{2\varepsilon_s q N_A (2\Phi_f)}}{C_{ox}} - \frac{qQ_M}{C_{ox}}$$



alkali ions (Na, K, ...)
in gate oxide

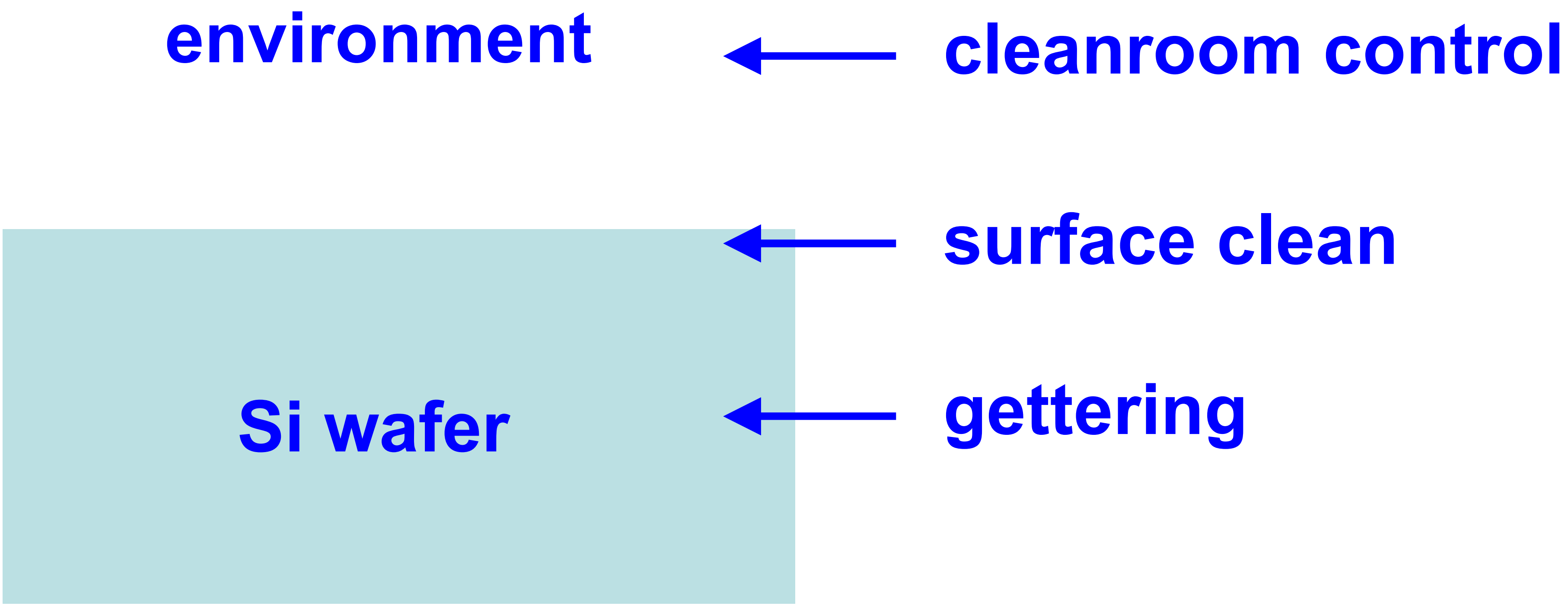
Defects on Surface





Surface roughness reduces breakdown voltages (E_{bd})

Defects Control

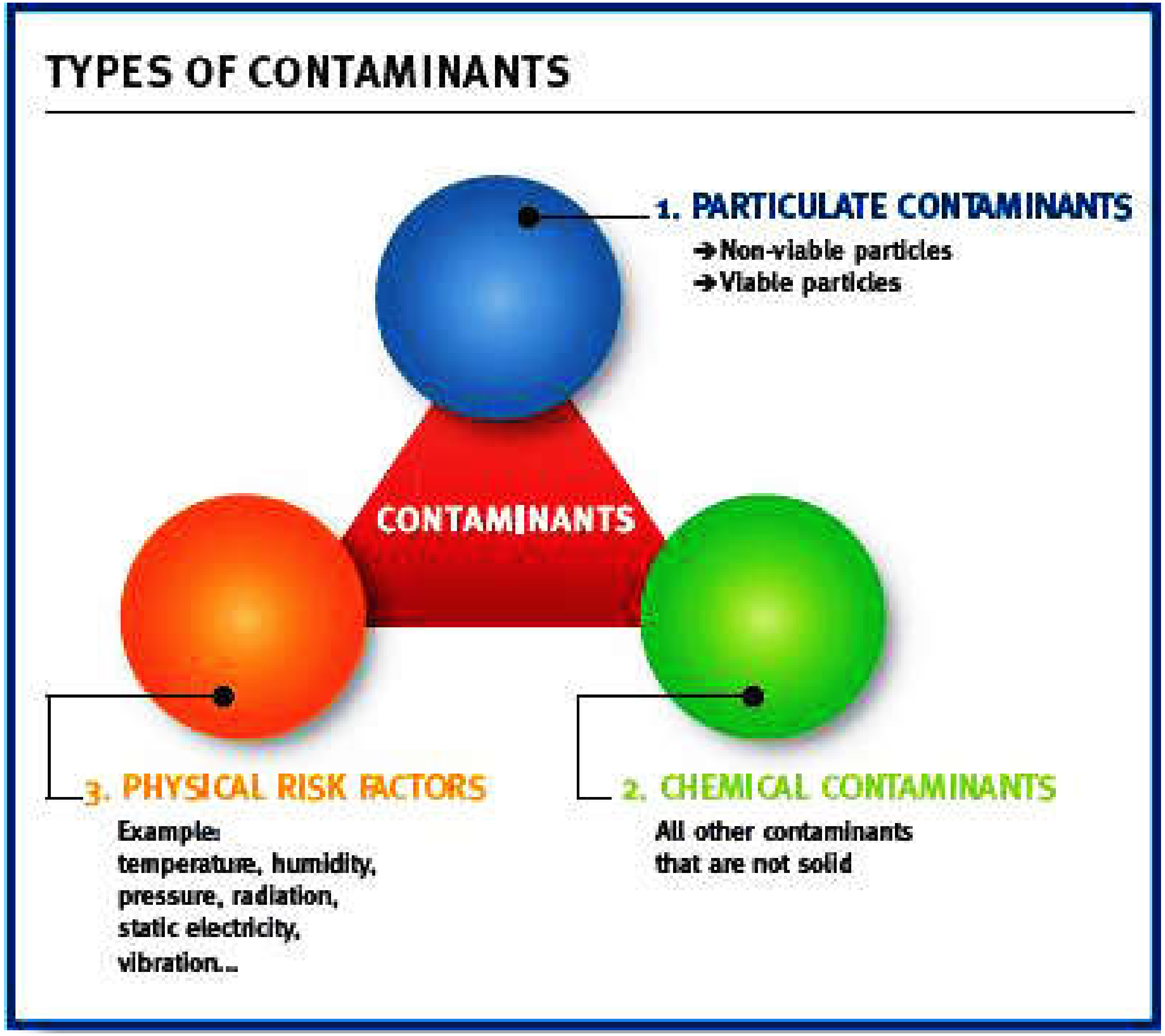


environment ← cleanroom control

surface clean

Si wafer ← gettering

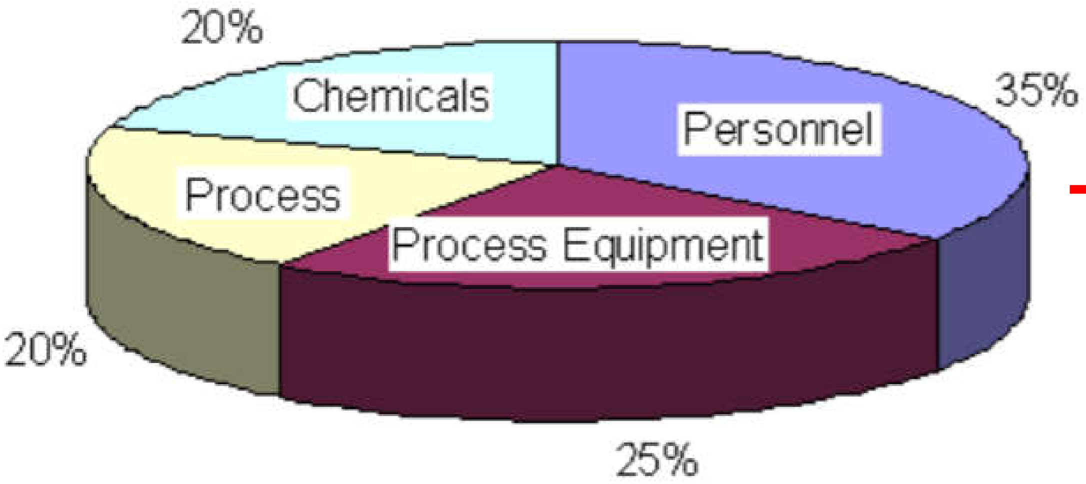
Contaminations



particles:
- hair
- pollen
- bacteria
- PM2.5
- ...

chemicals:
- organics
- Cu, Au
- Na, K
- ...

Sources of Contaminations



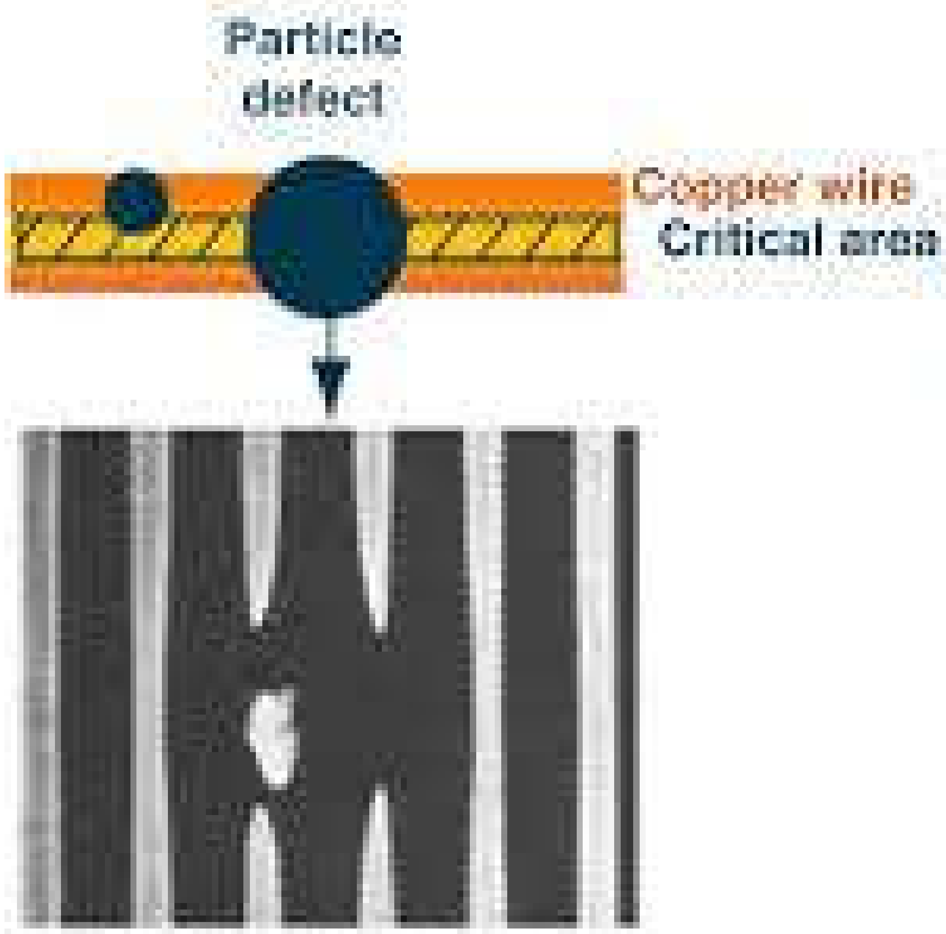
→ particles from human

sitting
100,000 /min

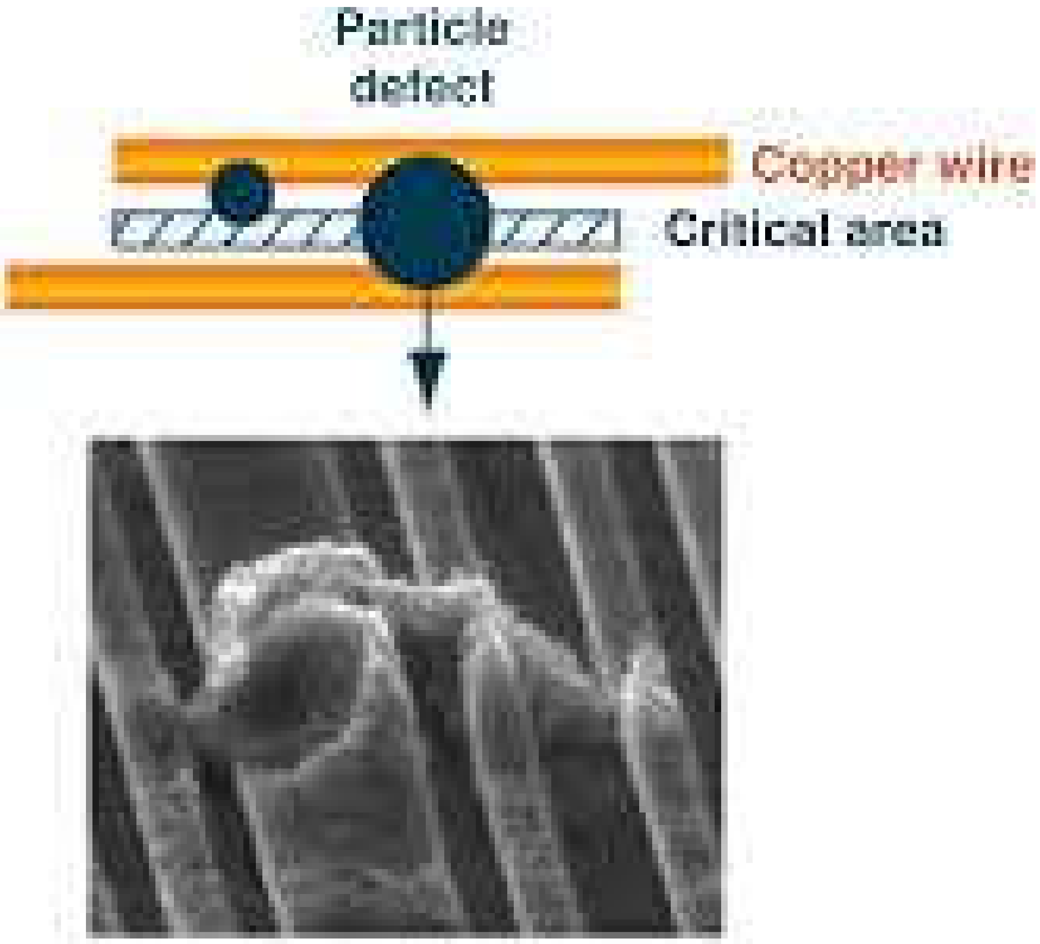
walking
1,000,000 /min

running
10,000,000 /min

Particles



Open circuit

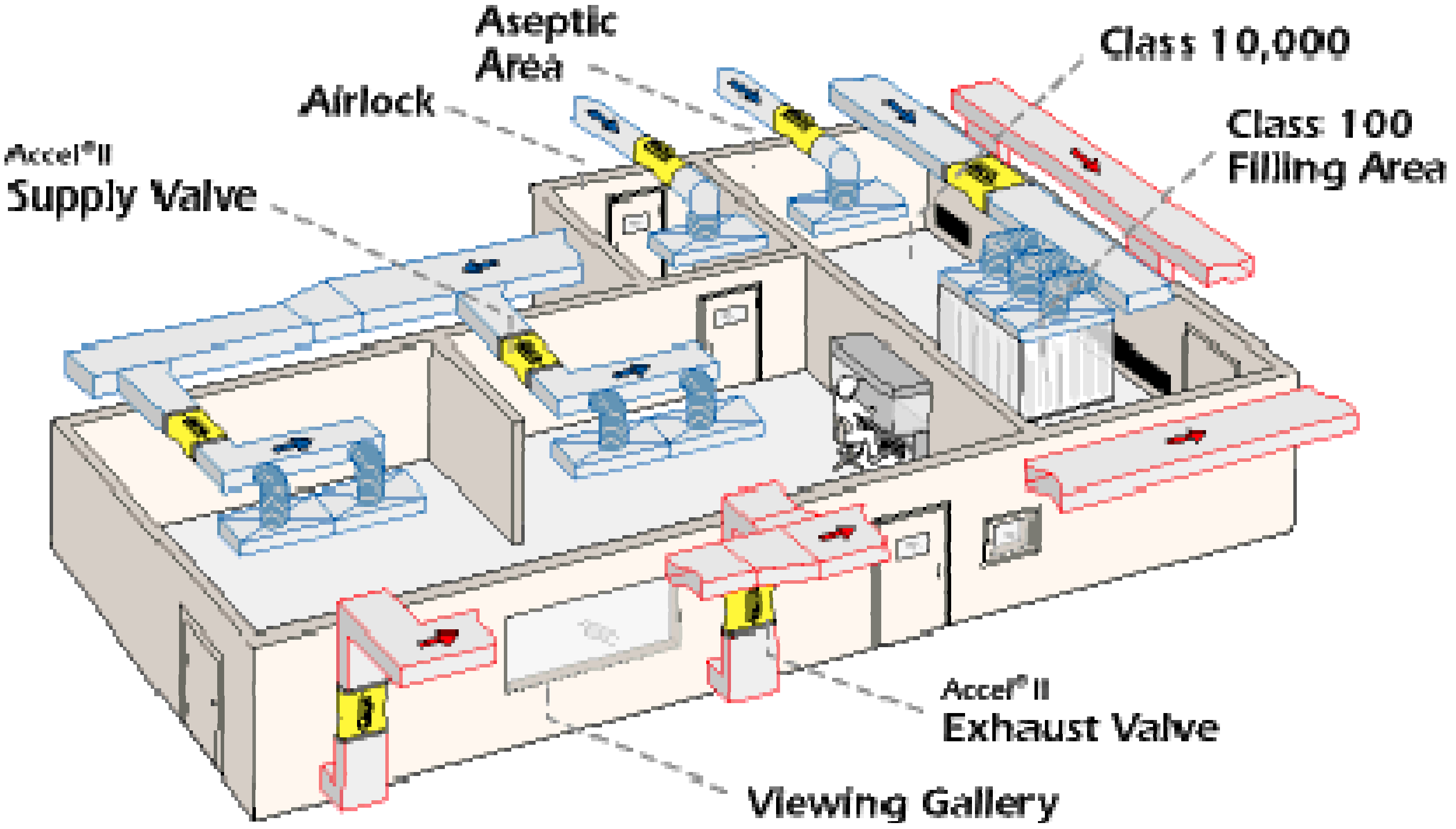


Short circuit

IC Roadmap

Year of 1st DRAM Shipment	1997	1999	2003	2006	2009	2012
Minimum Feature Size	250nm	180nm	130nm	100nm	70nm	50nm
Wafer Diameter (mm)	200	300	300	300	450	450
DRAM Bits/Chip	256M	1G	4G	16G	64G	256G
DRAM Chip Size (mm^2)	280	400	560	790	1120	1580
Microprocessor Transistors/chip	11M	21M	76M	200M	520M	1.40B
Critical Defect Size	**125nm**	**90nm**	**65nm**	**50nm**	**35nm**	**25nm**
Starting Wafer Total LLS (cm^{-2})	**0.60**	**0.29**	**0.14**	**0.06**	**0.03**	**0.015**
DRAM GOI Defect Density (cm^{-2})	**0.06**	**0.03**	**0.014**	**0.006**	**0.003**	**0.001**
Logic GOI Defect Density (cm^{-2})	**0.15**	**0.15**	**0.08**	**0.05**	**0.04**	**0.03**
Starting Wafer Total Bulk Fe (cm^{-3})	**3×10^{10}**	**1×10^{10}**	**Under 1×10^{10}**	**Under 1×10^{10}**	**Under 1×10^{10}**	**Under 1×10^{10}**
Metals on Wafer Surface After Cleaning (cm^{-2})	**5×10^9**	**4×10^9**	**2×10^9**	**1×10^9**	**$< 10^9$**	**$< 10^9$**
Starting Material Recombination Lifetime (µsec)	**≥ 300**	**≥ 325**	**≥ 325**	**≥ 325**	**≥ 450**	**≥ 450**

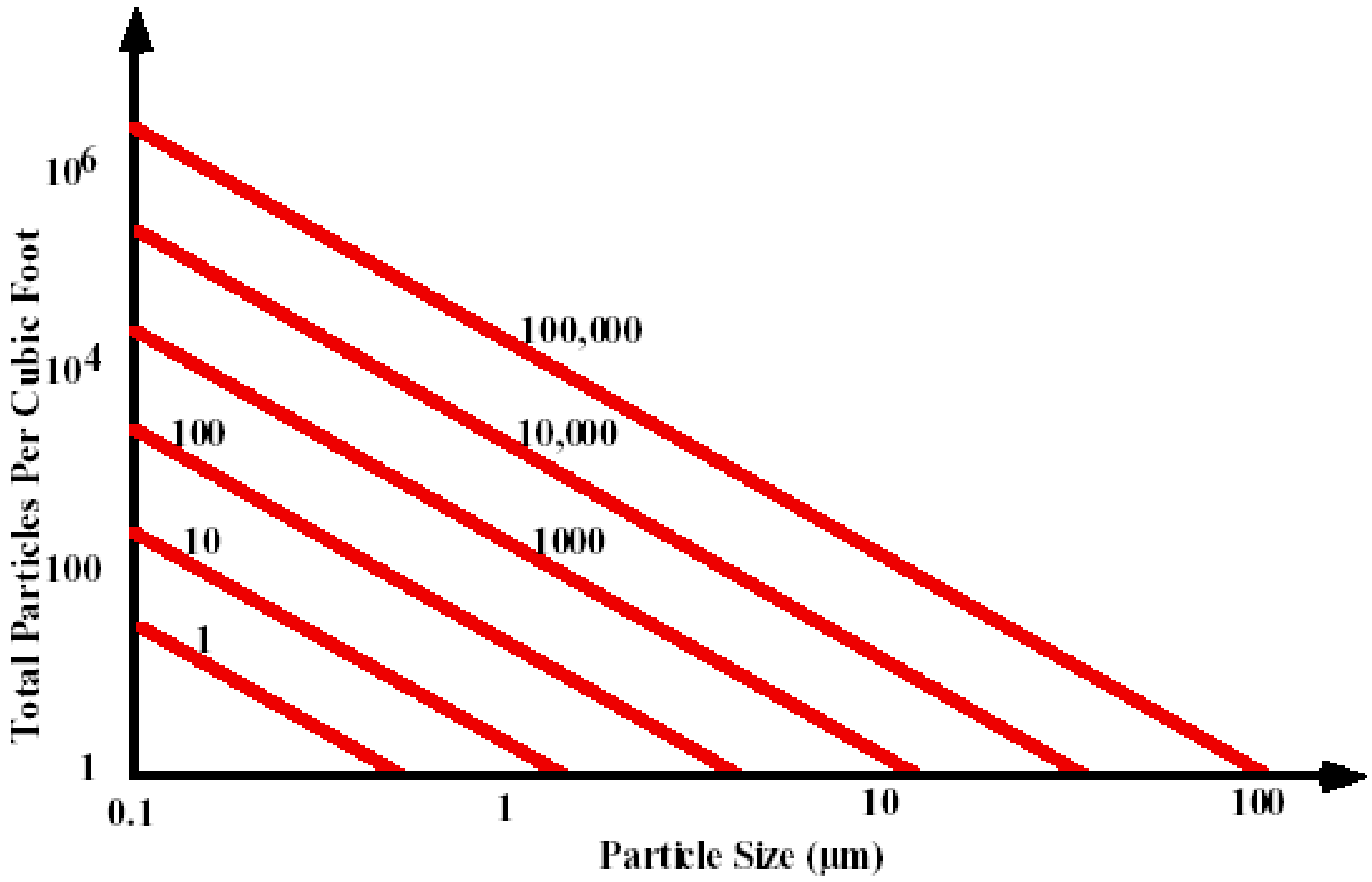
Cleanroom



class X:

less than X particles larger than 0.5 μm per cubic feet

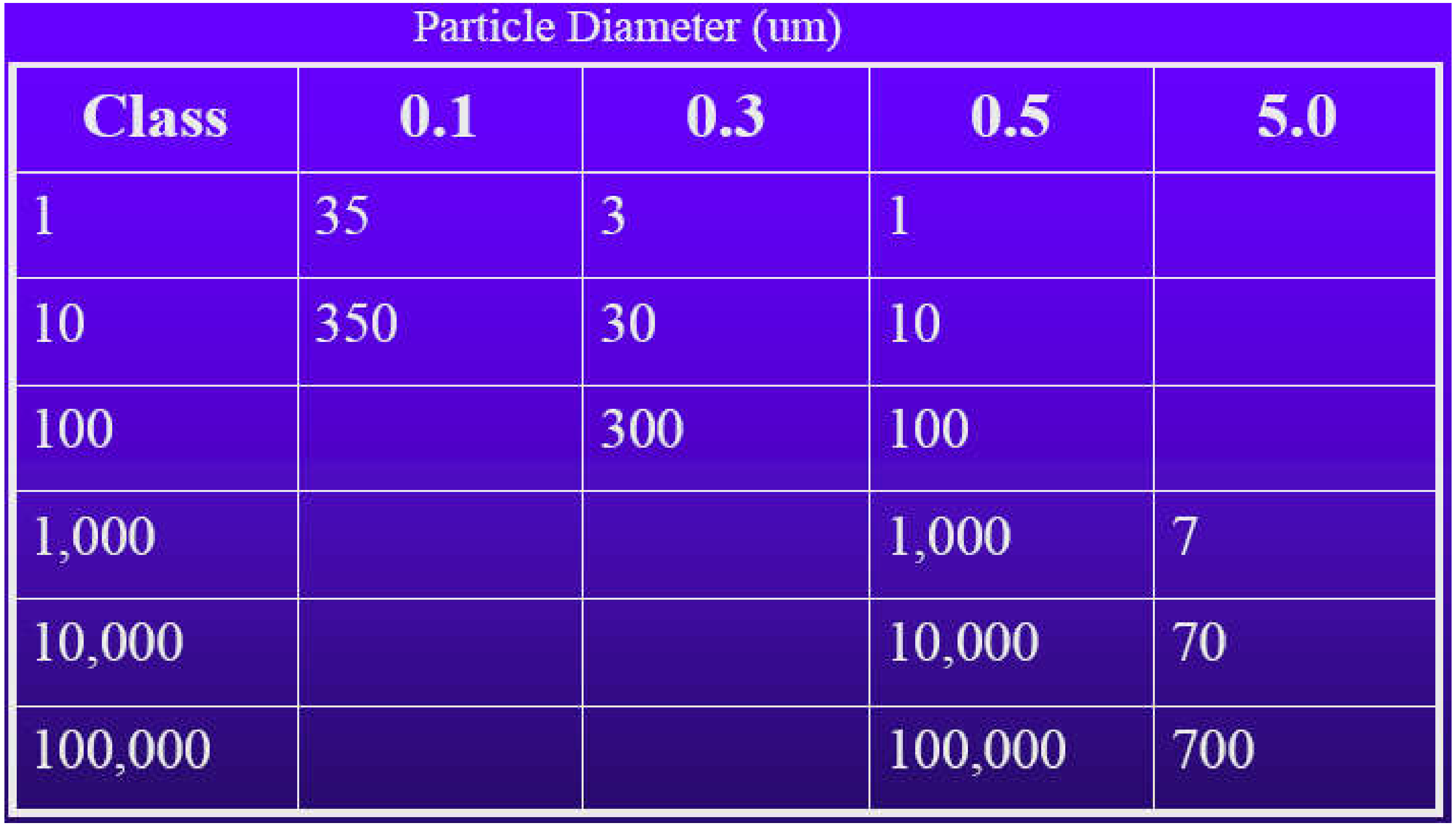
Cleanroom



class X:

less than X particles larger than 0.5 μm per cubic feet

Cleanroom



Particle Diameter (um)

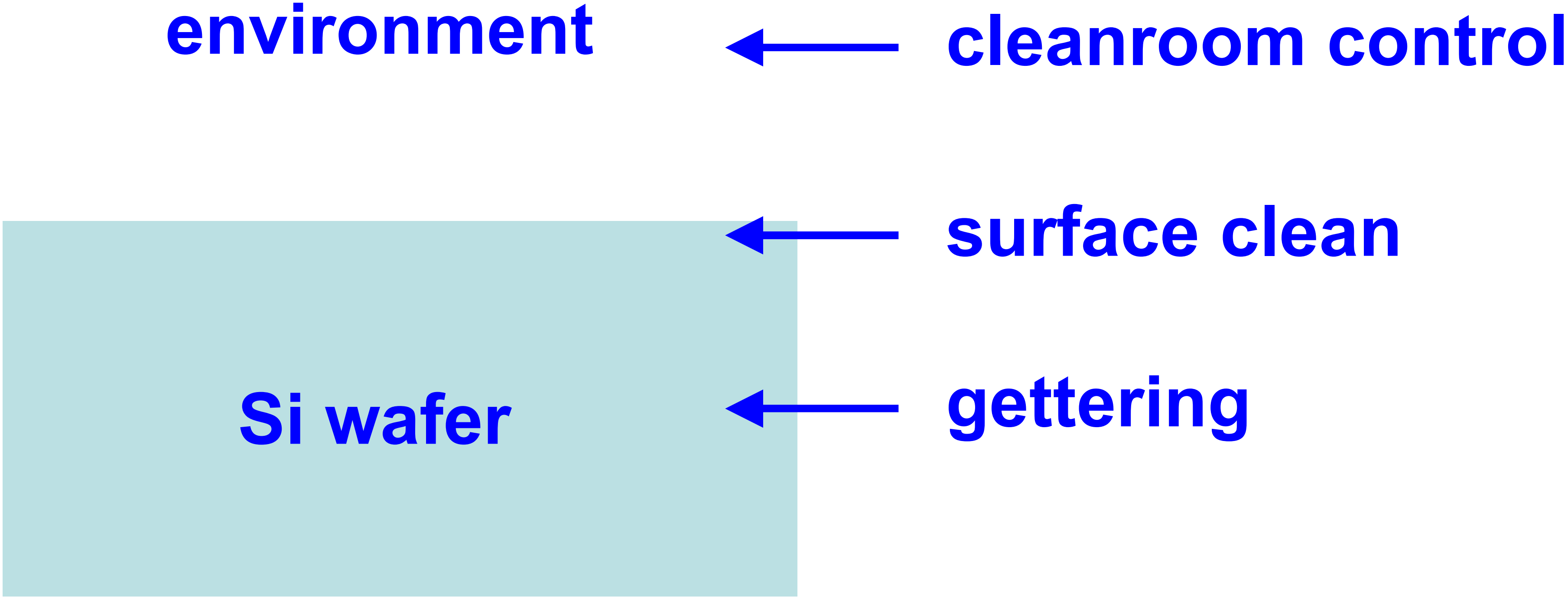
Class	0.1	0.3	0.5	5.0
1	35	3	1	
10	350	30	10	
100		300	100	
1,000			1,000	7
10,000			10,000	70
100,000			100,000	700

'PM2.5 index' << 1 μg/m^3

class X:

less than X particles larger than 0.5 μm per cubic feet

Defects Control



environment ← cleanroom control

surface clean

Si wafer ← gettering

Defects in Water

defects in water

effects of water cleaning on transistor performance

water resistivity (MΩ*cm, at 25 °C)	leakage current (A/μm²)
5	$12*10^{-9}$
10	$10*10^{-9}$
13	$5*10^{-9}$
15	$1*10^{-9}$

Water

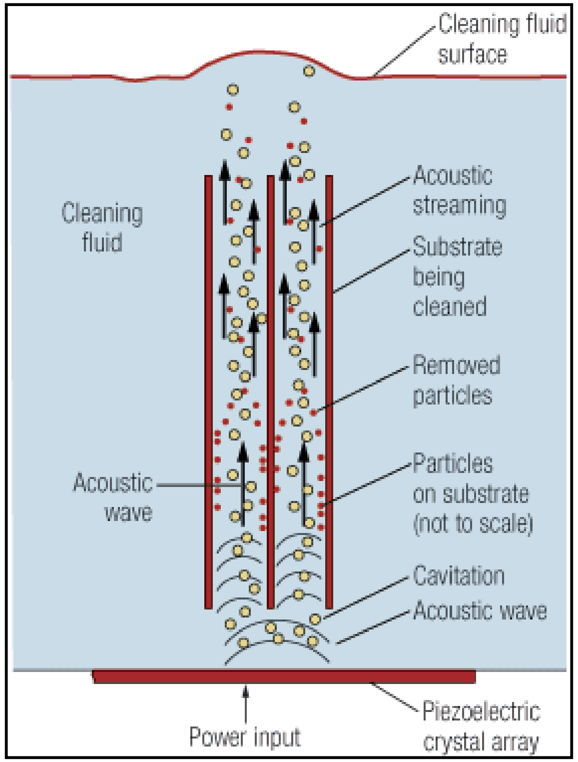
- Types
  - purified water, distilled water, tapping water, ...
  - 自来水，矿泉水，纯净水，超纯水，蒸馏水，...
- In cleanroom, deionized (DI) water (去离子水) is used
  - free of any mineral ions
  - only H^+, OH^-

$$H_2O <-> H^+ + OH^-$$

- In water, at 25 °C
  - $[H^+]*[OH^-] = K_w = 10^{-14}$ $(mol/L)^2$
  - in DI water, $[H^+] = [OH^-] = 10^{-7}$ mol/L, pH = 7.0
  - resistivity = 18.5 MΩ*cm

Si Wafer Clean

- **Ultrasonic / megasonic clean in DI water**



remove: large particles,
water soluble ions (Na, K, Cl, ...)

Standard Si Wafer Clean (RCA)

- Step 1 (SC-1)
  - $NH_4OH : H_2O_2 : H_2O = 1:1:5$, at 80 °C, 10 mins
  - remove organic residues
- Step 2
  - $HF : H_2O = 1:50$, at 25 °C, 20 secs
  - remove native SiO_2
- Step 3 (SC-2)
  - $HCl : H_2O_2 : H_2O = 1:1:6$, at 80 °C, 10 mins
  - remove metals
- Step 4
  - clean in DI water

https://en.wikipedia.org/wiki/RCA_clean

Metal Removal

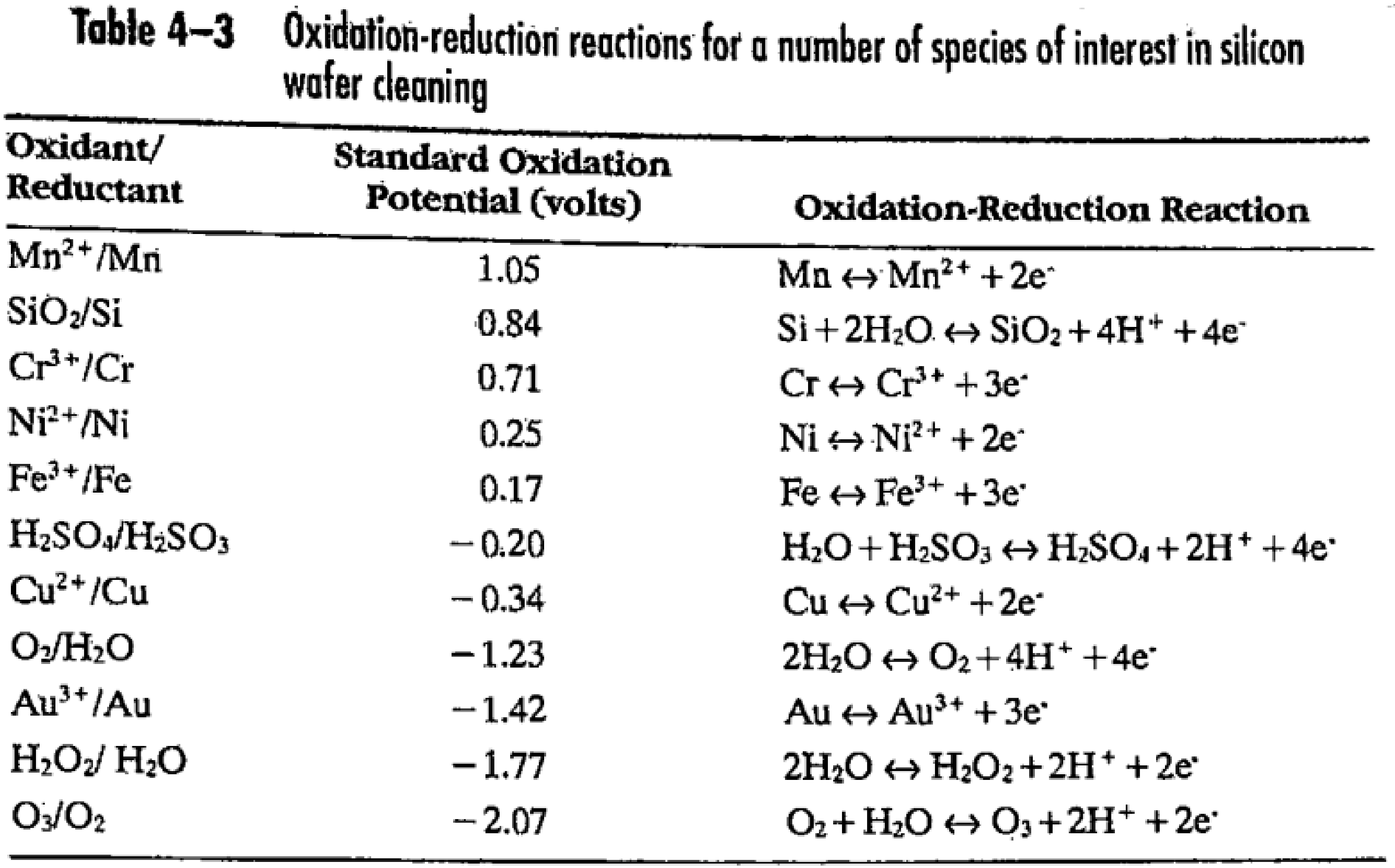


Table 4–3 Oxidation-reduction reactions for a number of species of interest in silicon wafer cleaning

Oxidant/ Reductant	Standard Oxidation Potential (volts)	Oxidation-Reduction Reaction
Mn^{2+}/Mn	1.05	$Mn \leftrightarrow Mn^{2+} + 2e^-$
SiO_2/Si	0.84	$Si + 2H_2O \leftrightarrow SiO_2 + 4H^+ + 4e^-$
Cr^{3+}/Cr	0.71	$Cr \leftrightarrow Cr^{3+} + 3e^-$
Ni^{2+}/Ni	0.25	$Ni \leftrightarrow Ni^{2+} + 2e^-$
Fe^{3+}/Fe	0.17	$Fe \leftrightarrow Fe^{3+} + 3e^-$
H_2SO_4/H_2SO_3	−0.20	$H_2O + H_2SO_3 \leftrightarrow H_2SO_4 + 2H^+ + 4e^-$
Cu^{2+}/Cu	−0.34	$Cu \leftrightarrow Cu^{2+} + 2e^-$
O_2/H_2O	−1.23	$2H_2O \leftrightarrow O_2 + 4H^+ + 4e^-$
Au^{3+}/Au	−1.42	$Au \leftrightarrow Au^{3+} + 3e^-$
H_2O_2/H_2O	−1.77	$2H_2O \leftrightarrow H_2O_2 + 2H^+ + 2e^-$
O_3/O_2	−2.07	$O_2 + H_2O \leftrightarrow O_3 + 2H^+ + 2e^-$

Other Si Clean Recipes

- Piranha clean
  - SPM: Sulfuric-Peroxide Mixture
  - $H_2SO_4 : H_2O_2 = 3:1$, 10–30 mins
  - extremely exothermic, self heating up to 80 °C
  - remove organic residues and some metals

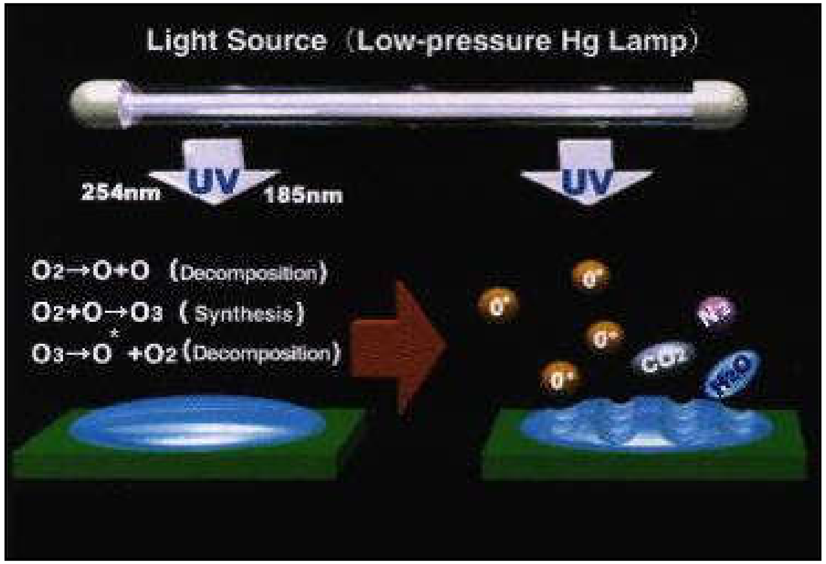
- Ozone (O_3) clean
  - $H_2O + O_3$
  - remove organic residues

'wet' method

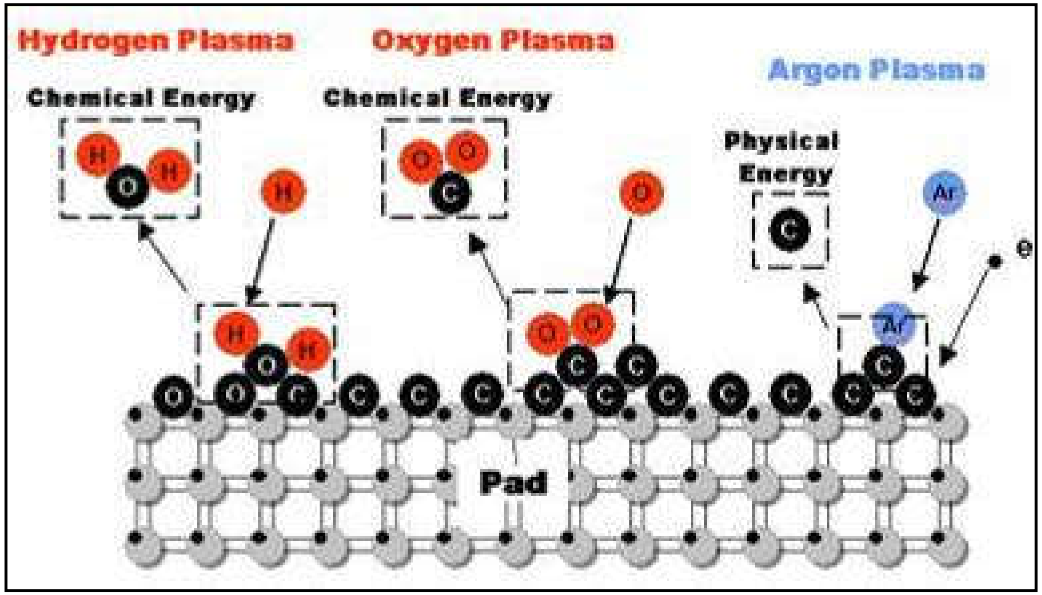
- Organic solvent
  - Acetone / Isopropanol / DI water
  - remove organic residues
  - not used for standard CMOS process!

Other Si Clean Recipes

- **UV Ozone clean**
  - clean organic residues



- **Plasma clean**
  - clean organic residues

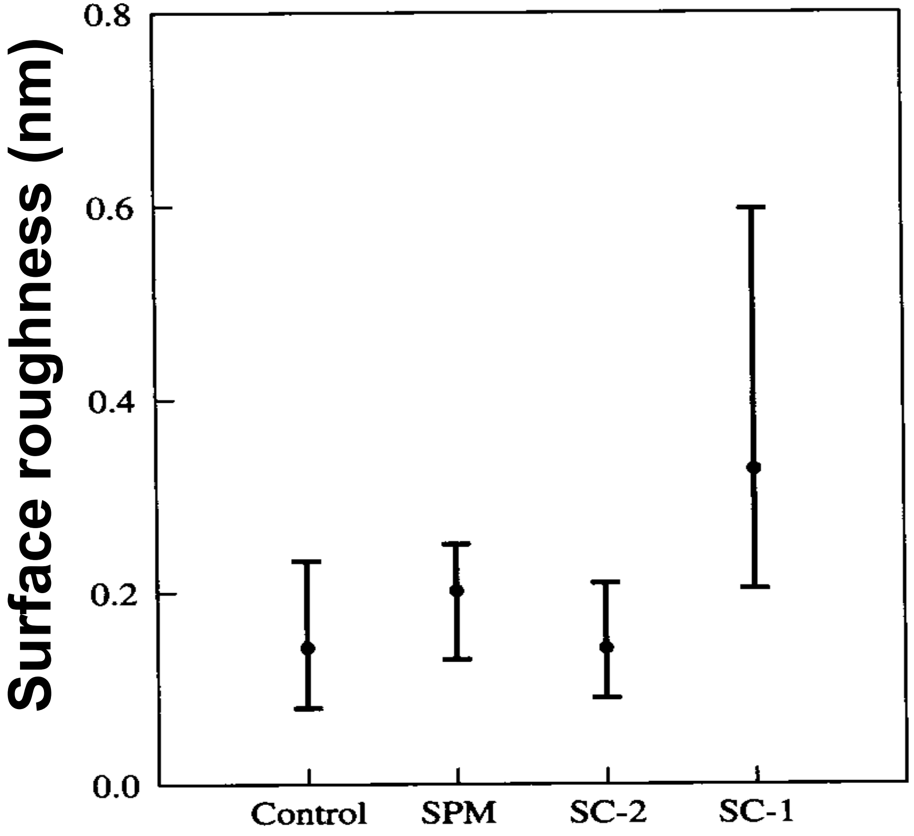


'dry' method

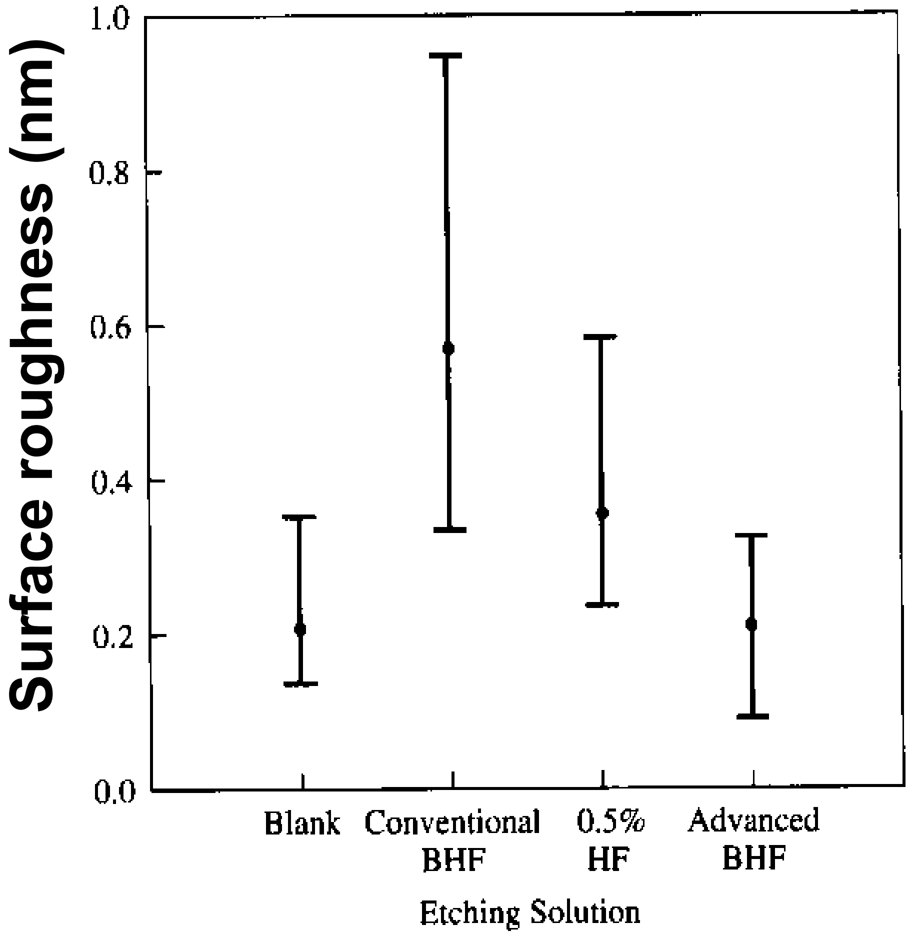
Clean other Materials

- SiO_2 (glass, quartz, ...)
  - piranha clean, H_2SO_4 : H_2O_2 = 3:1, 10–30 mins
  - SC-1, NH_4OH : H_2O_2 : H_2O = 1:1:5, at 80 °C, 10 mins
- GaAs
  - NH_4OH : H_2O = 1:10, for stoichiometric surface (Ga/As 1:1)
  - H_3PO_4 or HCl, for As rich surface
- Acetone / Isopropanol / DI water
  - generally works well for most non-CMOS process

Surface Roughness

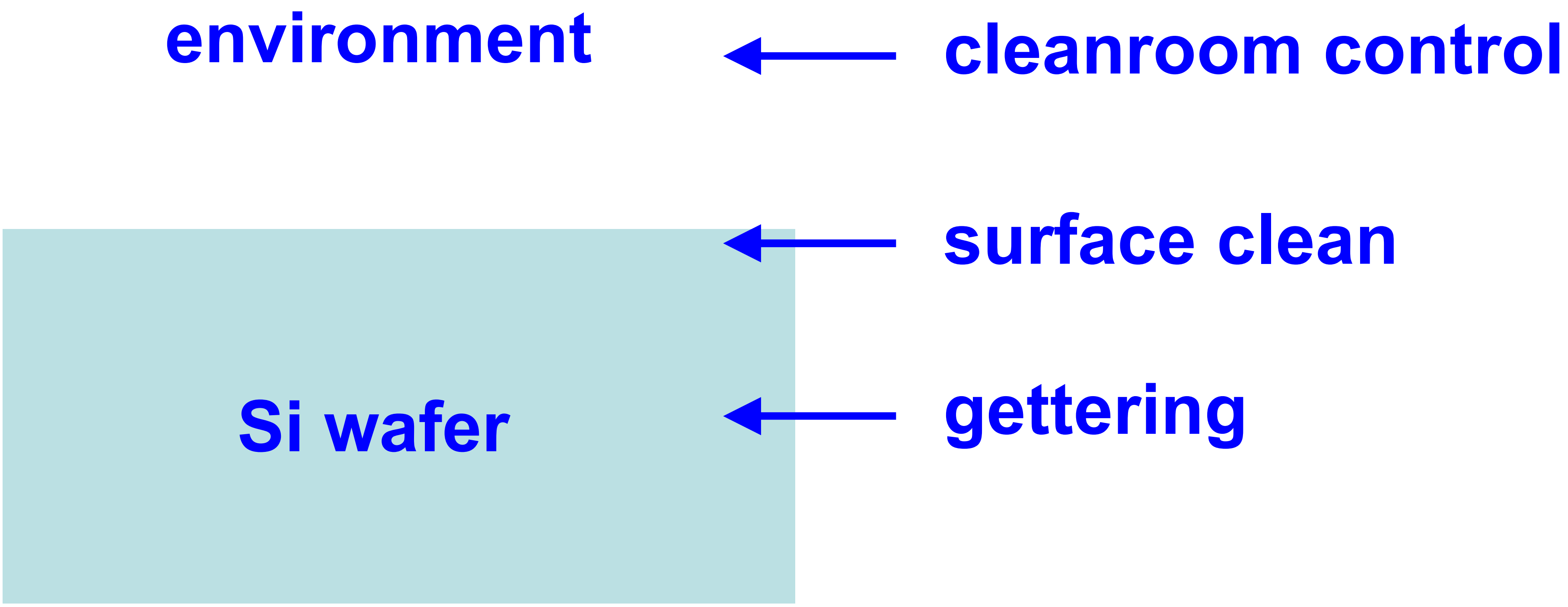


SPM: H_2SO_4–H_2O_2 cleaning
SC-1: NH_4OH–H_2O_2–H_2O cleaning
SC-2: HCl–H_2O_2–H_2O cleaning



Surface Roughness of Si after cleaning
ammonia (NH_4OH) and HF slightly etches Si

Defects Control



environment

cleanroom control

surface clean

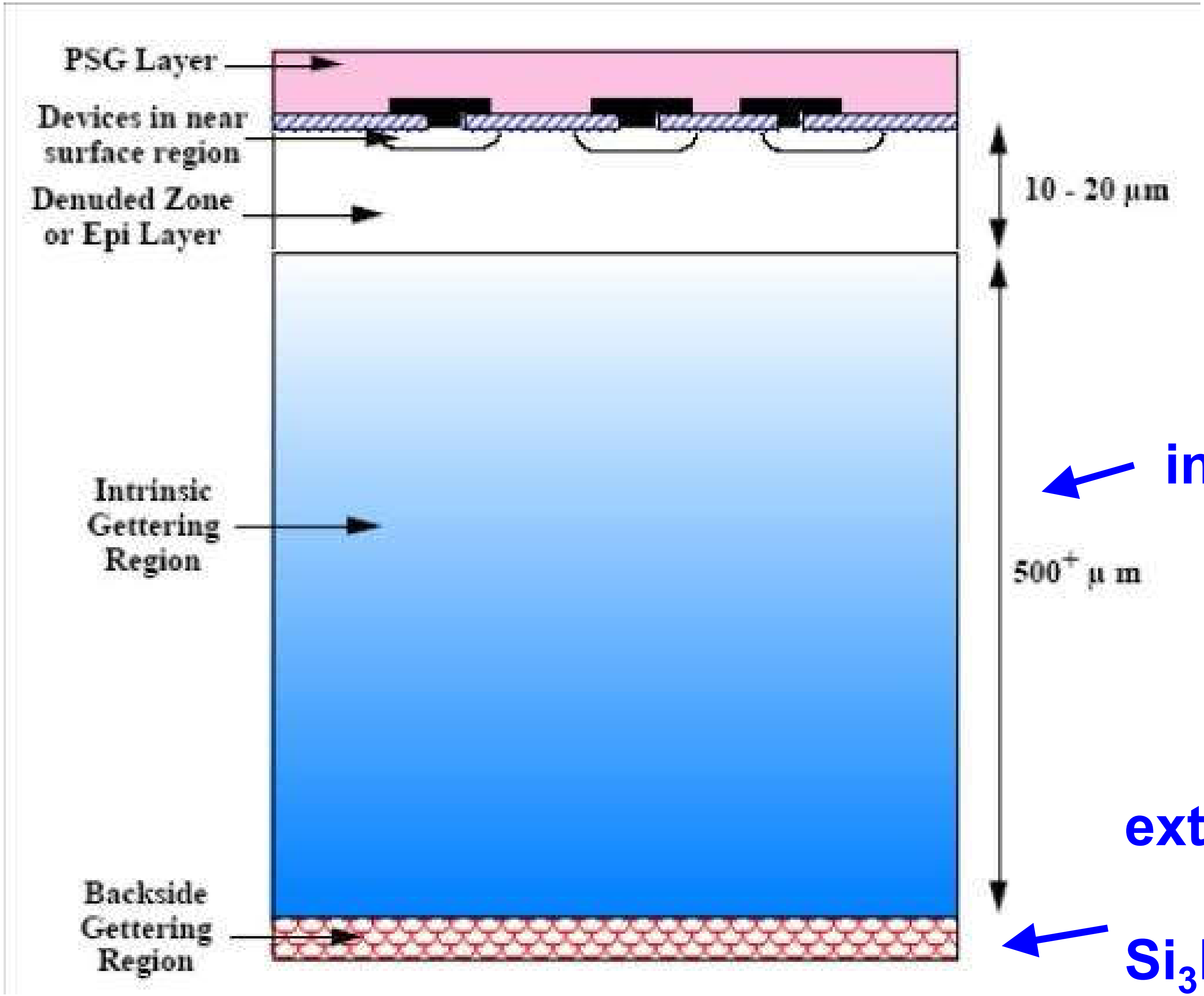
Si wafer

gettering

Gettering（吸杂）

- 'gettering' in the vacuum tube
  - use titanium to absorb gases in vacuum tubes

Si Wafer Gettering（吸杂）



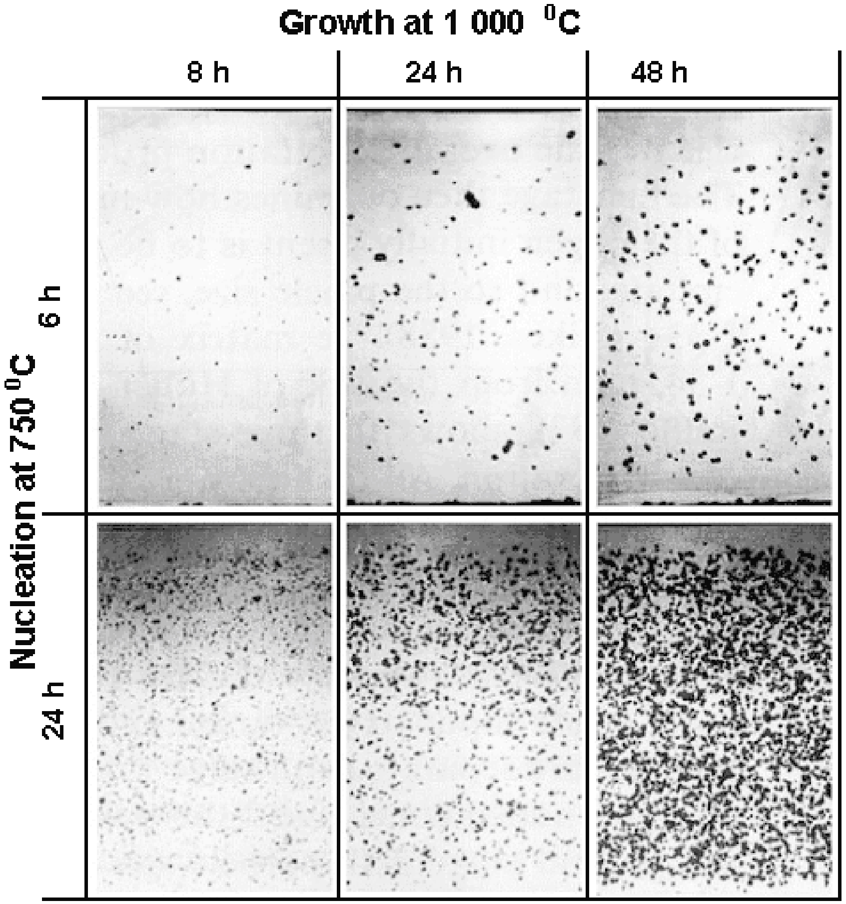
intrinsic gettering

extrinsic gettering:

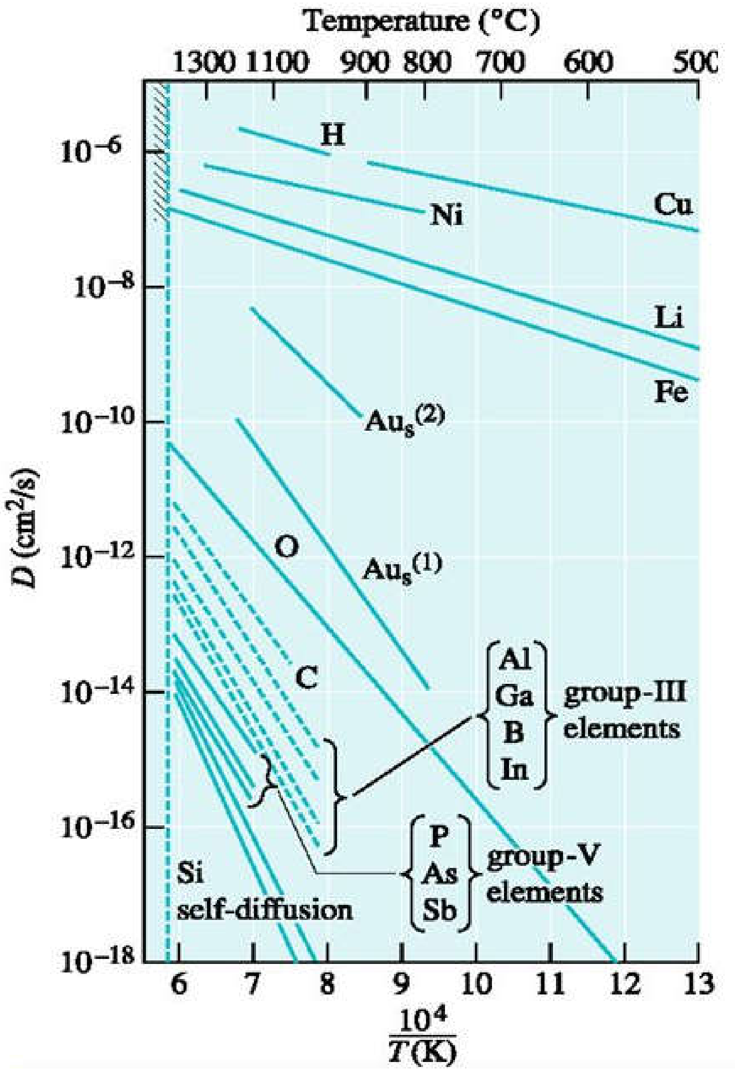
Si_3N_4, P_2O_5, ...

Si Wafer Gettering（吸杂）

- **intrinsic gettering**



O defects in Si



easy

hard

diffusivity of defects

Si Wafer Gettering（吸杂）

- **Minority carrier lifetime**

Au doped Si:	**10^{-9} s**
Typical Si:	**10^{-6} s**
Gettered Si:	**10^{-3} s**

Principles of Micro- and Nanofabrication for Electronic and Photonic Devices

Lab Safety

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Lab Safety

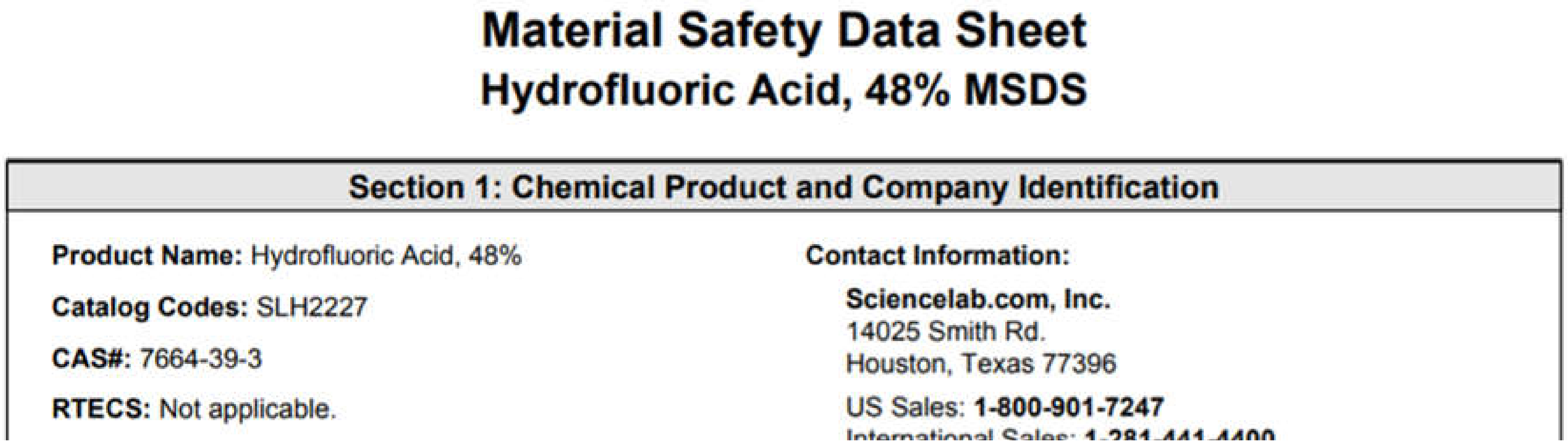
- Chemicals
  - HF, H_2SO_4, ...
  - KOH, NH_4OH, ...
  - Acetone, ...
- Electricity
  - instruments, ...
- Fires
  - Acetone, Alcohol, ...
- Sharps
  - silicon, glass, ...
- ...

Lab Safety

- Lab orientation
  - exits, showers, …
- Proper protection
  - gloves, goggles, aprons, …
- Materials Data Safety Sheets (MSDS)
- …

Lab Safety

- **Materials Data Safety Sheets (MSDS)**



Material Safety Data Sheet
Hydrofluoric Acid, 48% MSDS

Section 1: Chemical Product and Company Identification

Product Name: Hydrofluoric Acid, 48%

Catalog Codes: SLH2227

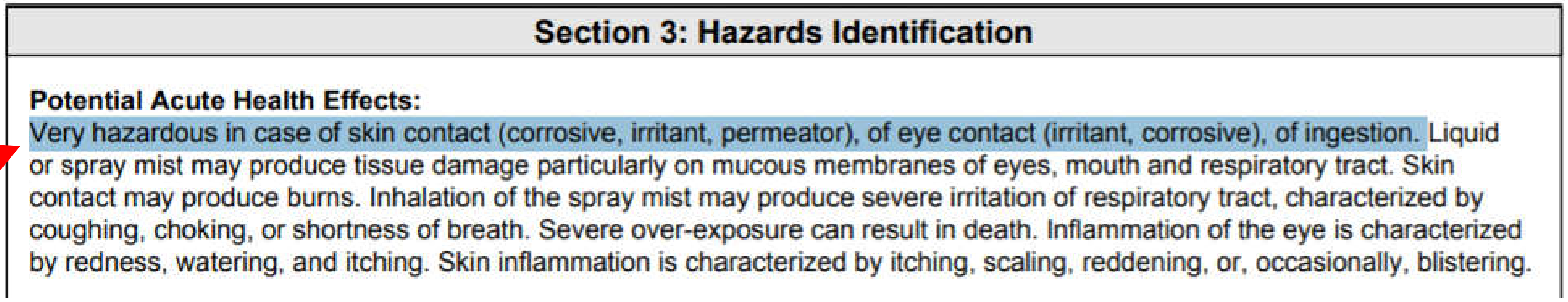
CAS#: 7664-39-3

RTECS: Not applicable.

Contact Information:

Sciencelab.com, Inc.
14025 Smith Rd.
Houston, Texas 77396

US Sales: **1-800-901-7247**
International Sales: **1-281-441-4400**



Section 3: Hazards Identification

Potential Acute Health Effects:
Very hazardous in case of skin contact (corrosive, irritant, permeator), of eye contact (irritant, corrosive), of ingestion. Liquid or spray mist may produce tissue damage particularly on mucous membranes of eyes, mouth and respiratory tract. Skin contact may produce burns. Inhalation of the spray mist may produce severe irritation of respiratory tract, characterized by coughing, choking, or shortness of breath. Severe over-exposure can result in death. Inflammation of the eye is characterized by redness, watering, and itching. Skin inflammation is characterized by itching, scaling, reddening, or, occasionally, blistering.

Chemical Safety

- NFPA diamond
  - 0: no hazard
  - 4: highest risk

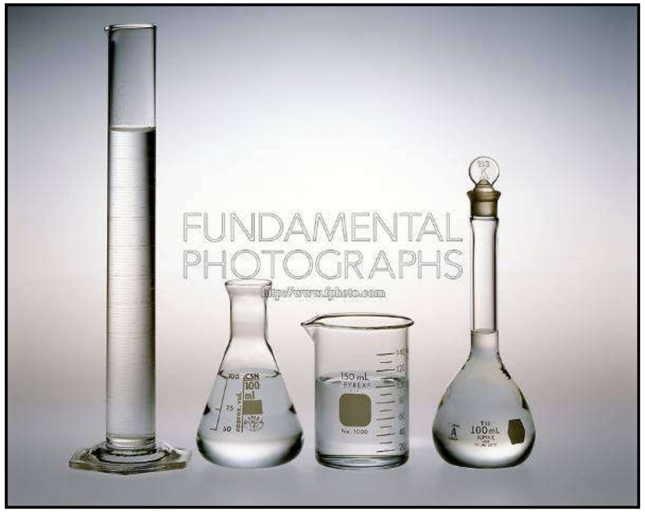
HF

acetone

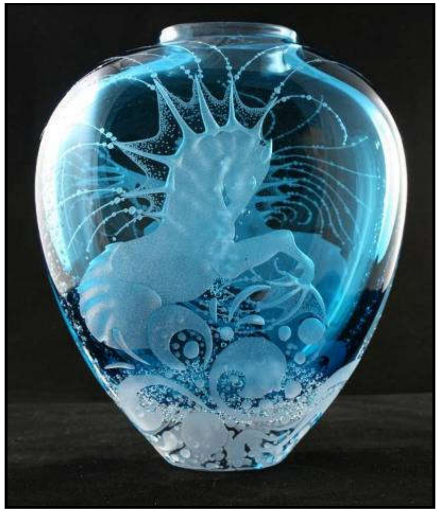
H_2O_2

Chemical Safety

- Choose proper containers
- Most solvents
  - glass, Teflon, ...



- Be careful
  - alkali (NaOH, etc) slowly etches glass
  - HF strongly etches glass!



glass art by HF etch

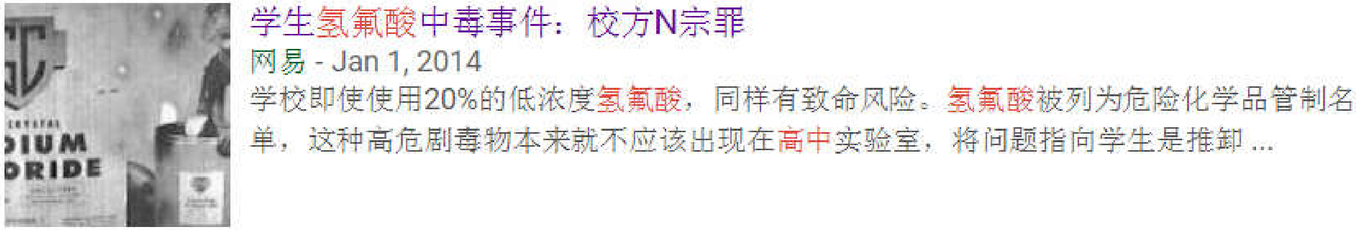
Chemical Safety

宣城郎溪中学化学备课组举办玻璃画制作比赛

2011年01月11日11时08分　来源： 中安教育网 分享到

为提高学生学习化学兴趣，增强学生的动手能力，激发学生思维发散能力。日前，宣城郎溪中学高一化学备课组举办玻璃画制作比赛，百余人参加了此次活动。图为玻璃画制作现场。(宗京能)

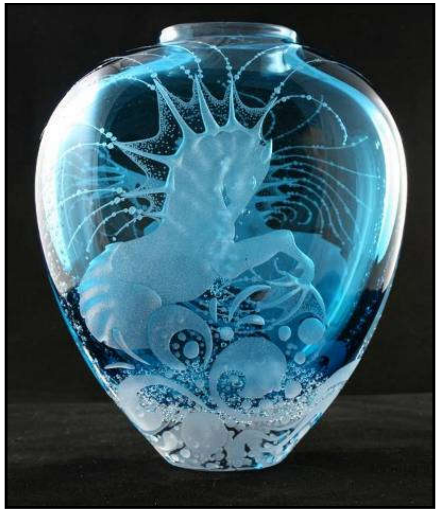
编辑： 李其平



学生氢氟酸中毒事件：校方N宗罪

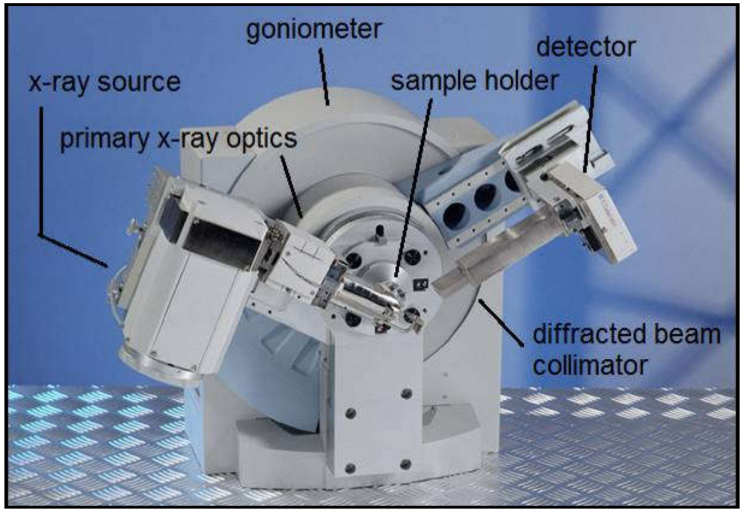
网易 - Jan 1, 2014

学校即使使用20%的低浓度氢氟酸，同样有致命风险。氢氟酸被列为危险化学品管制名单，这种高危剧毒物本来就不应该出现在高中实验室，将问题指向学生是推卸 ...

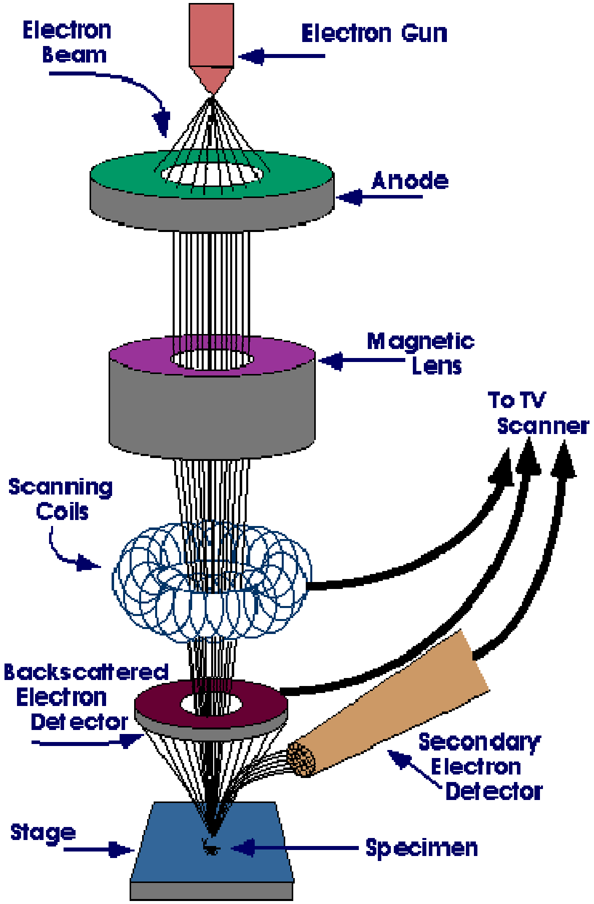


glass art by HF etch

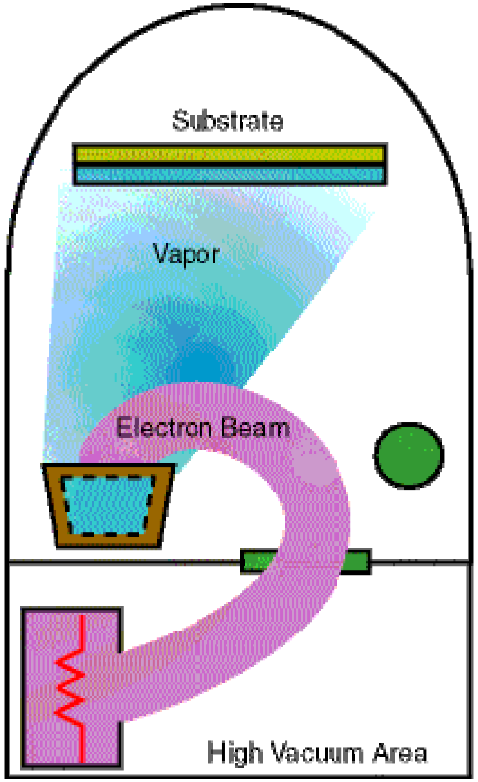
Radiation Safety



XRD



SEM & TEM



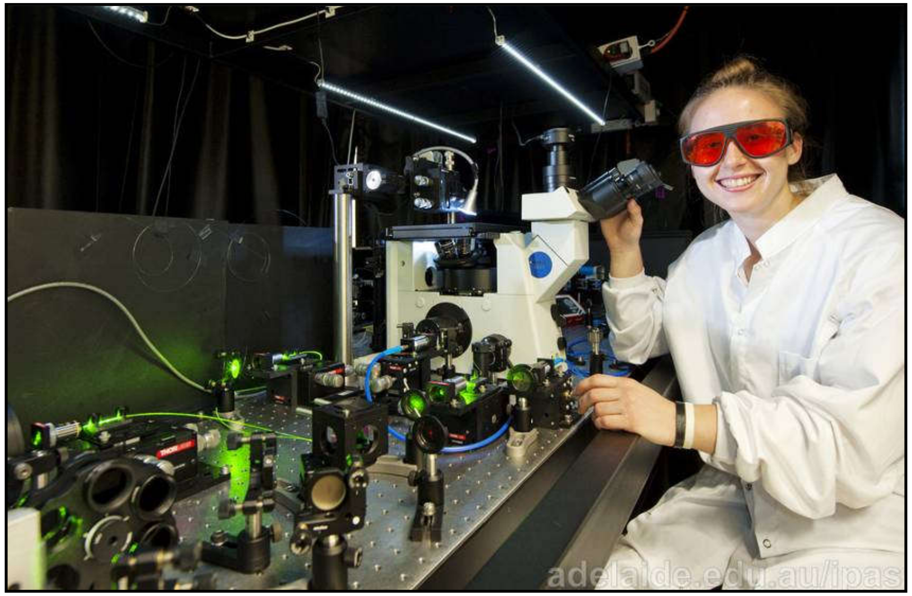
Ebeam Evaporator

Laser Safety

Class 1	CD/DVD Player/Recorder, Laptop or Personal Computer
Class 2	Presentation Laser Pointer, Barcode Reader
Class 3R	Some Measuring & Targeting Devices, Higer Power Pointers
Class 3B	Higher power laser products intened for professional applications
Class 4	Medical Lasers, Industrial Cutting/Welding, Scientific Applications and most *Laser Light Show* Equipment

wear goggles

Q: O.D.



Biological Safety

Basic Facility

- BSL-1
  - Safe microorganisms
  - Not known to cause disease in healthy adult humans
- BSL-2
  - Moderate-risk microorganisms
  - Potentially hazard to humans and the environment
  - e.g. inactivated virus that Causes Foot and Mouth Disease

Containment Facility

- BSL-3, BSL-3 Enhanced & BSL-3 Ag
  - High-risk microorganisms, foreign and emerging agents
  - Serious and potential lethal consequences for livestock
  - Not harmful to humans because of protective measures
  - e.g. live virus that Causes Foot and Mouth Disease
- BSL-4
  - High-risk agents microorganisms
  - No known vaccine or therapy
  - e.g. Nipah and Hendra viruses

Cleanroom Orientation

Video

always gown up!

Process References

https://cleanroom.byu.edu